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Bhaumik

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(54) **INSTRUMENT REPROCESSOR AND
INSTRUMENT REPROCESSING METHODS**

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Related U.S. Application Data

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(51) **Int. Cl.**

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A61L 2/24 (2006.01)
A61L 2/18 (2006.01)
B08B 3/04 (2006.01)

(Continued)

(52) **U.S. Cl.**

CPC **A61L 2/24** (2013.01); **A61B 1/123** (2013.01); **A61B 1/125** (2013.01); **A61B 90/70** (2016.02); **A61L 2/18** (2013.01); **B08B 3/04** (2013.01); **B08B 9/00** (2013.01); **G05D 16/2013** (2013.01); **A61B 2090/701** (2016.02); **Y10T 137/7761** (2015.04); **Y10T 137/8601** (2015.04)

(58) **Field of Classification Search**

None

See application file for complete search history.

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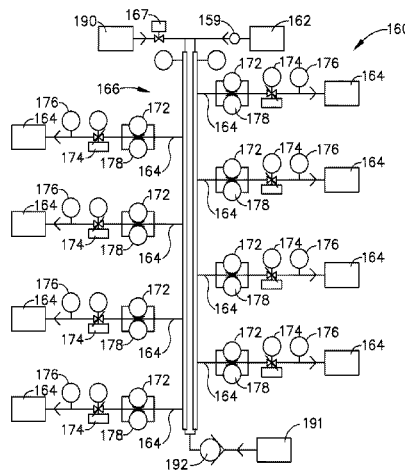
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(57) **ABSTRACT**

An instrument reprocessor for cleaning, disinfecting, and/or sterilizing a medical instrument is disclosed. To reprocess instruments having one or more channels defined therein, the reprocessor can include one or more flow control systems configured to control a flow of fluid through each channel. In various embodiments, a flow control system can include a differential pressure sensor and a proportional valve for controlling the fluid flow in a channel. The reprocessor can also include, one, a fluid circulation pump which can be configured to supply the flow control systems with fluid and, two, a system for controlling the pressure of the fluid supplied to the flow control systems. The reprocessor can also include a system for supplying a metered amount of fluid to the fluid circulation system. The system can include a reservoir having a fluid height sensor to monitor the amount of fluid therein and a pump configured to supply the reservoir with fluid.

11 Claims, 18 Drawing Sheets



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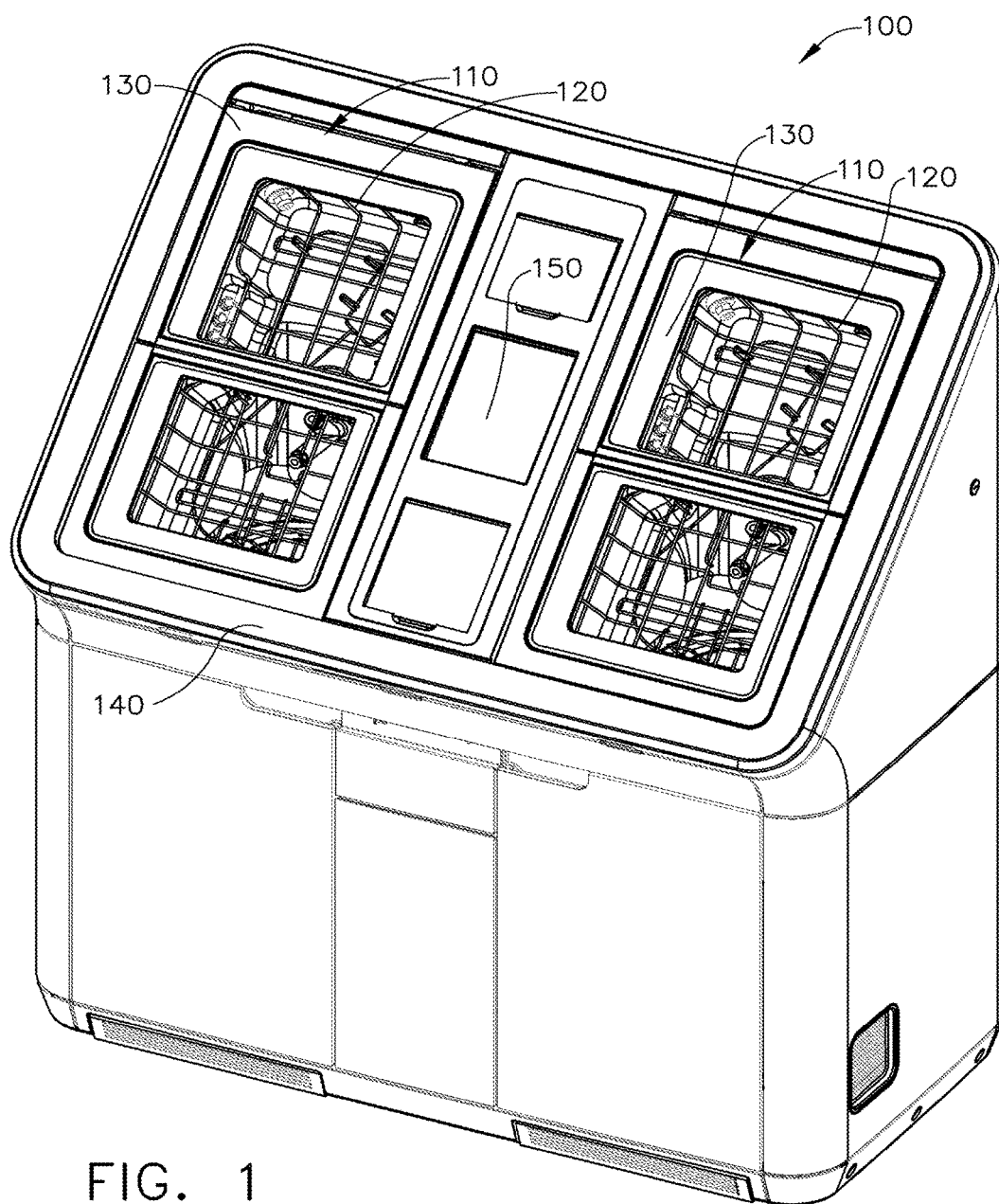


FIG. 1

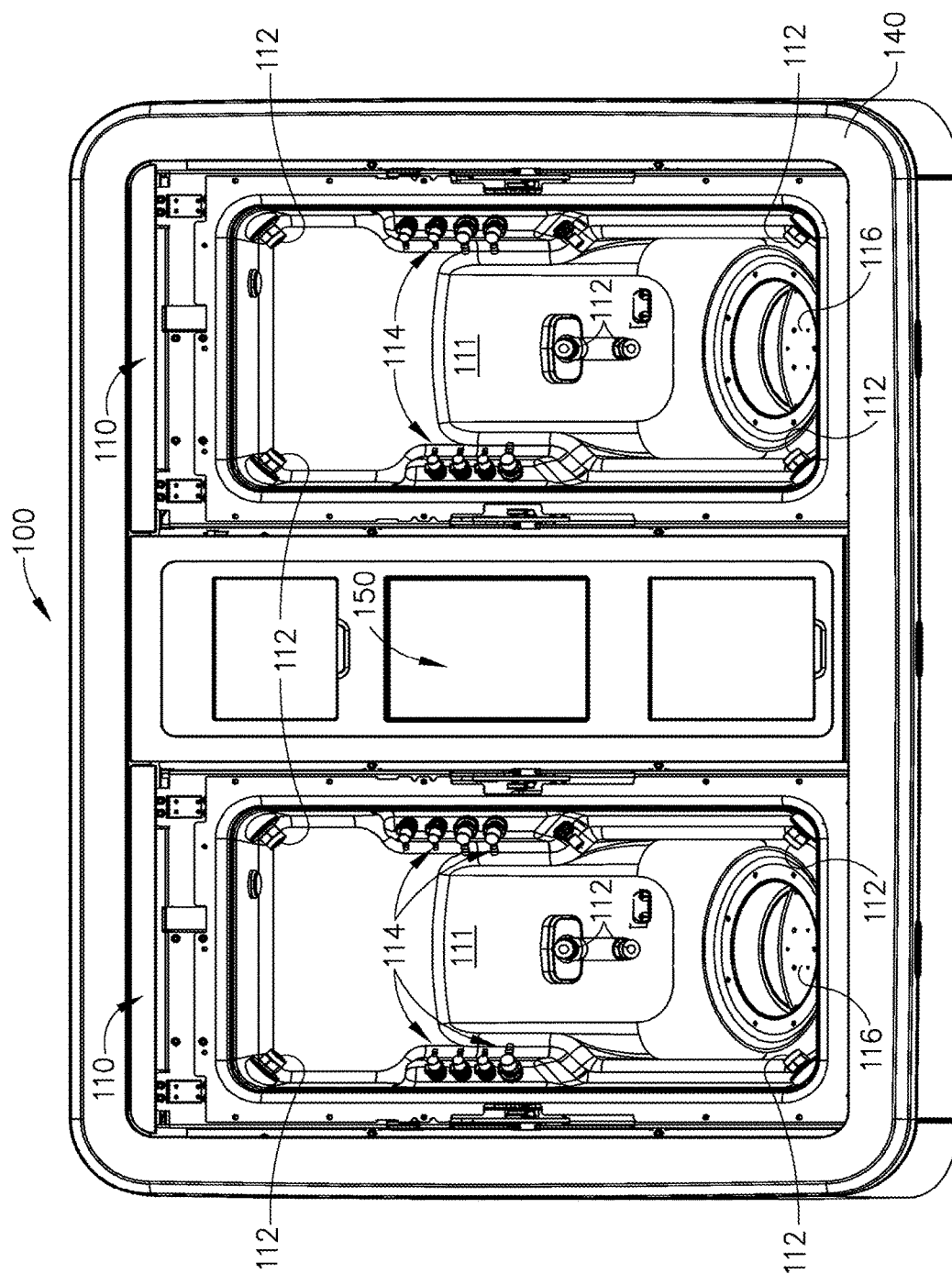


FIG. 2

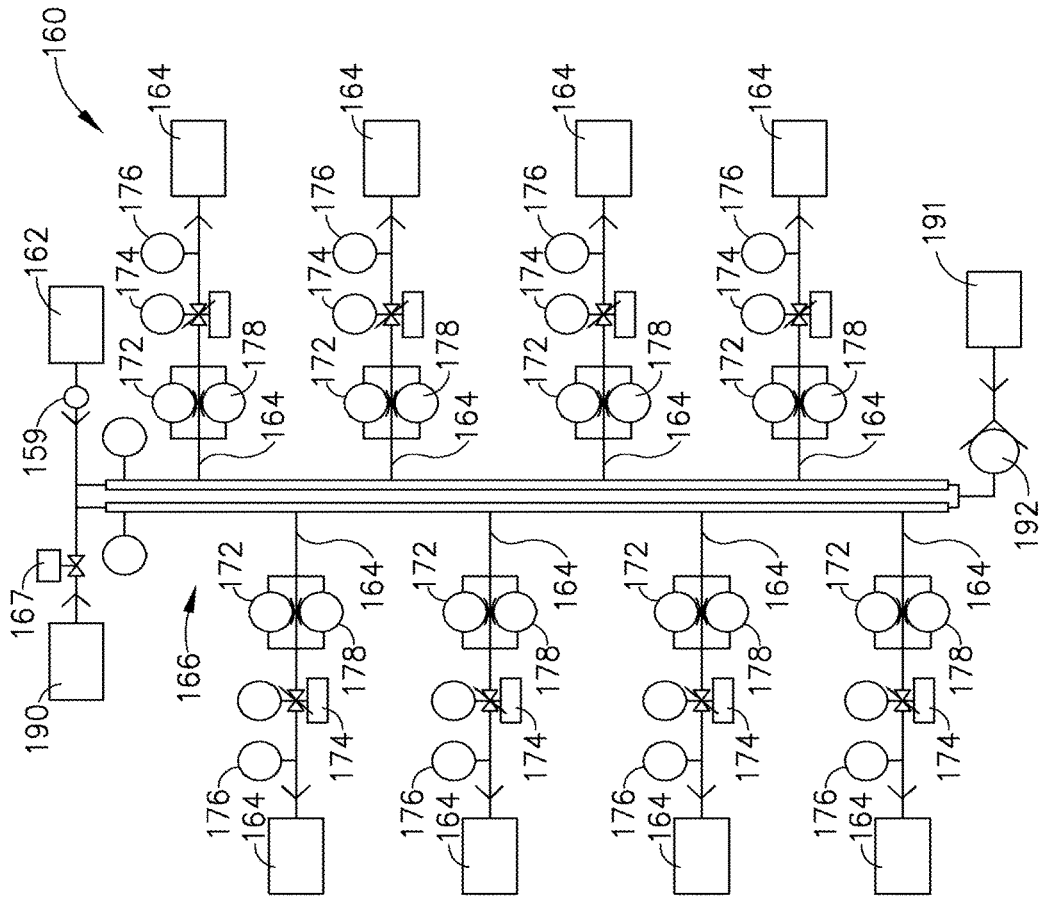


FIG. 3

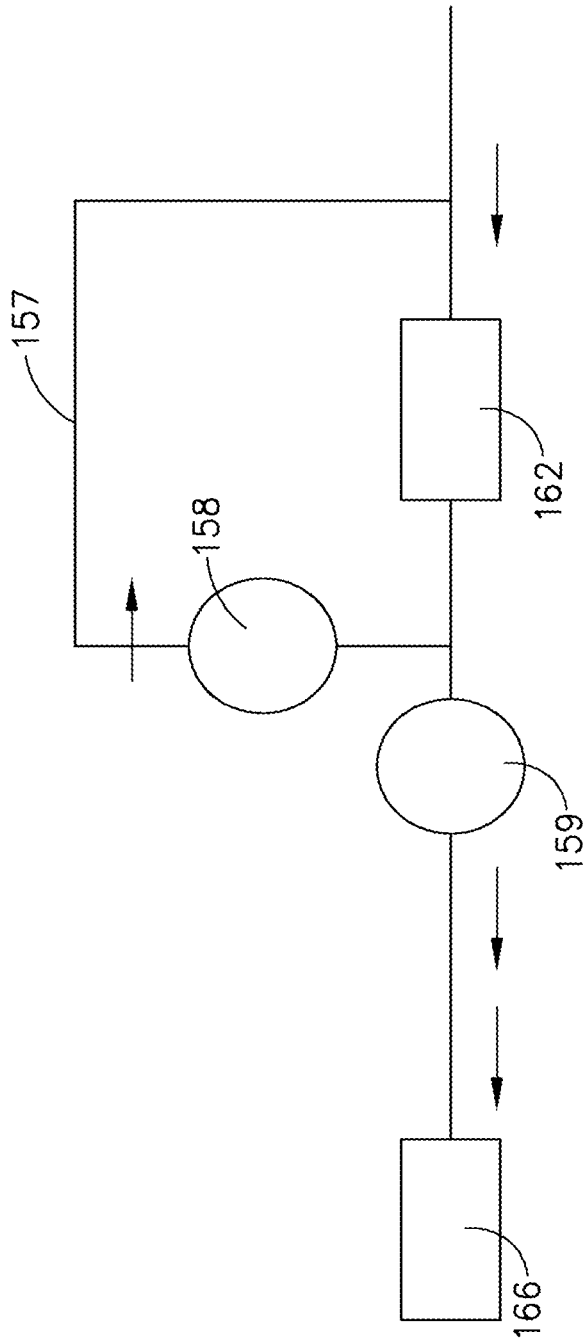


FIG. 3A

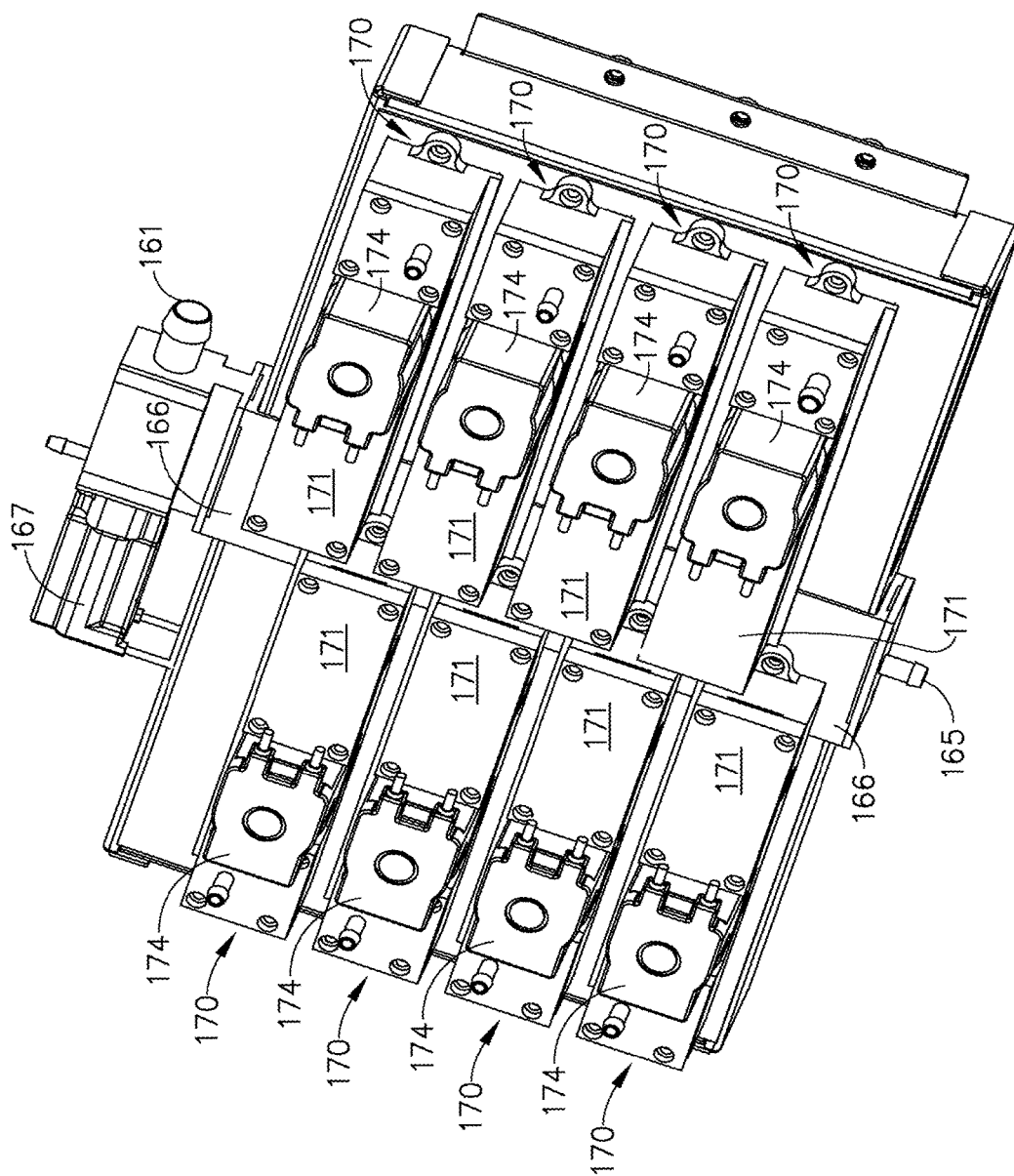


FIG. 4

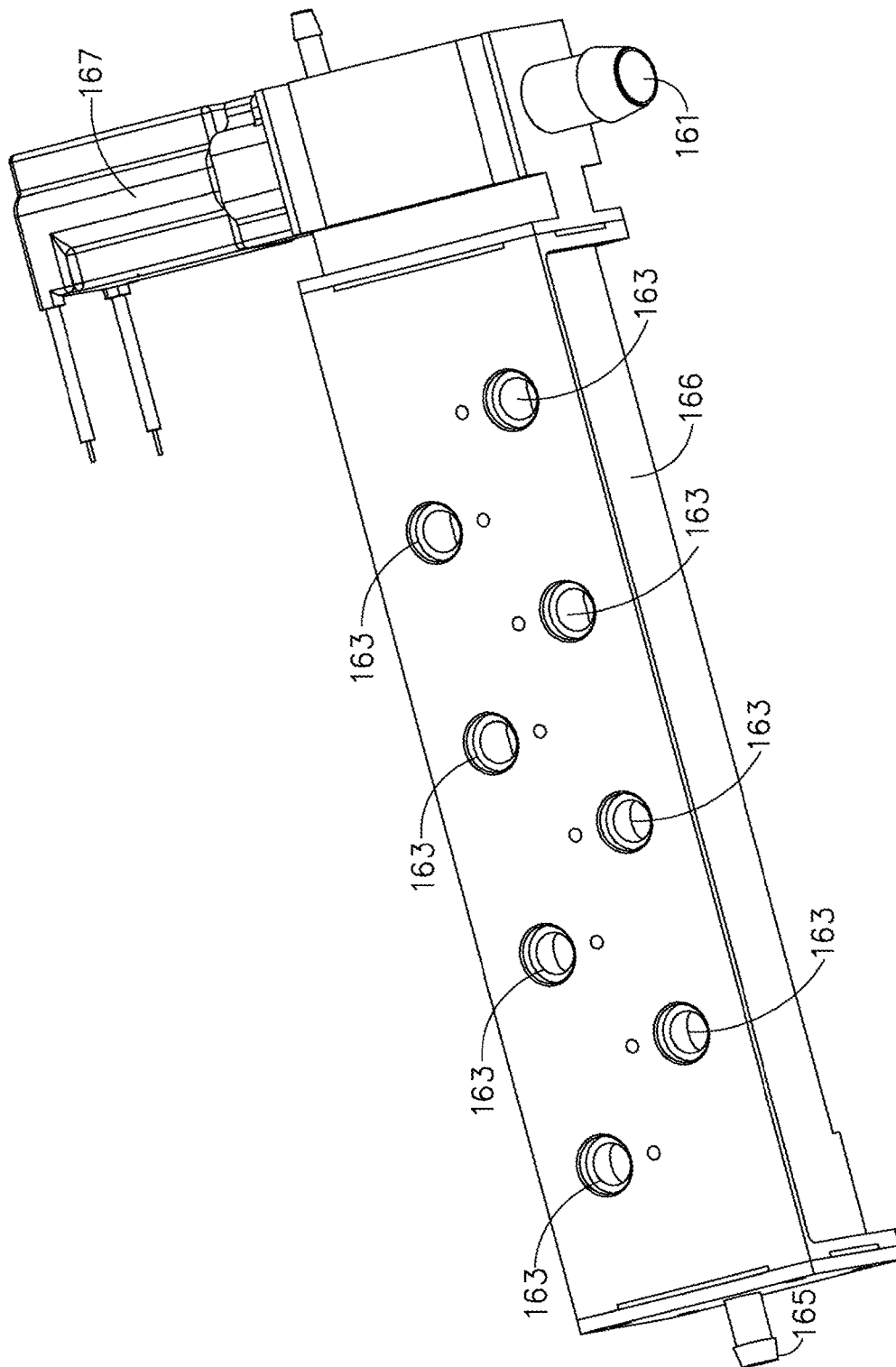


FIG. 5

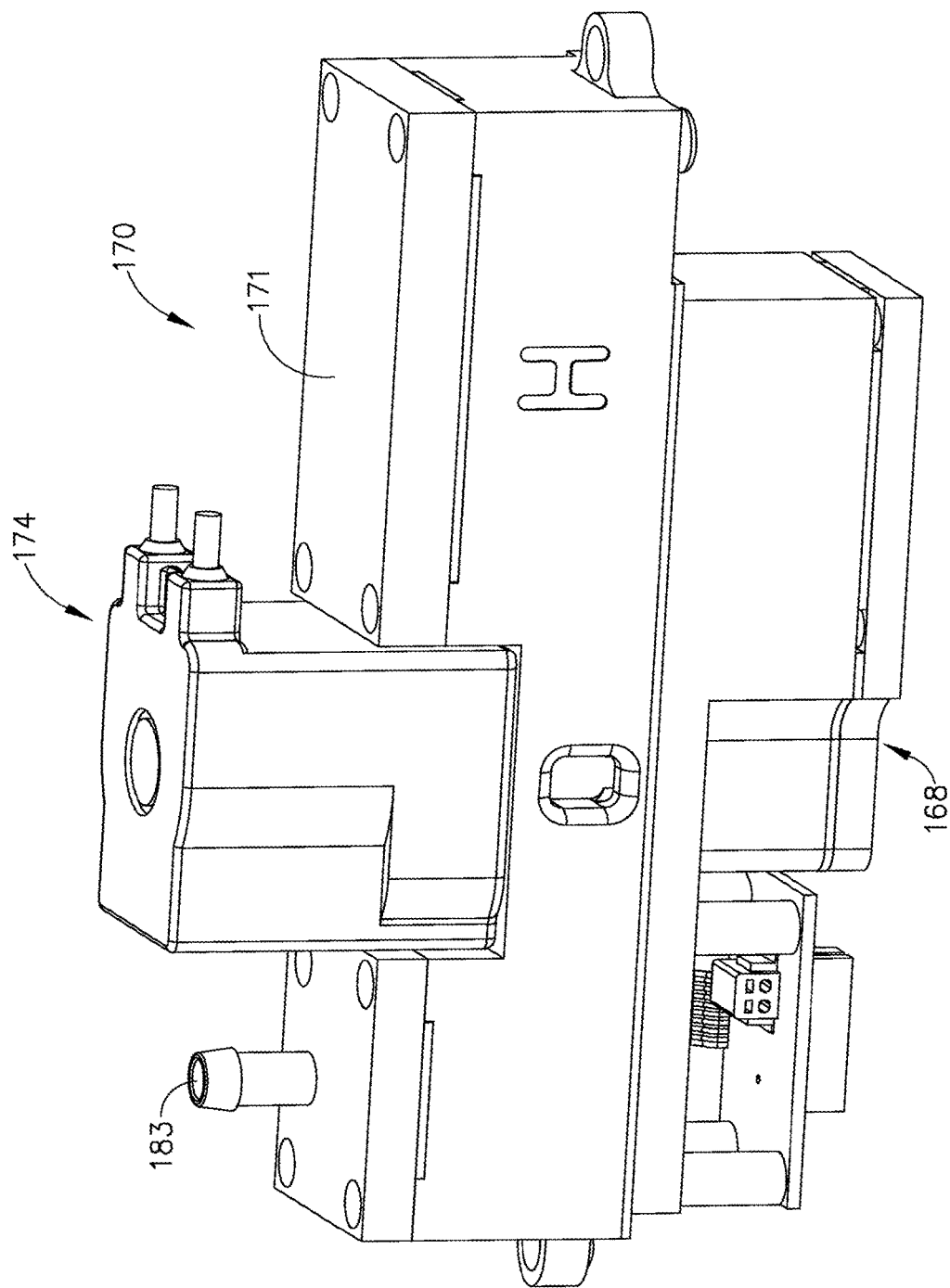


FIG. 6

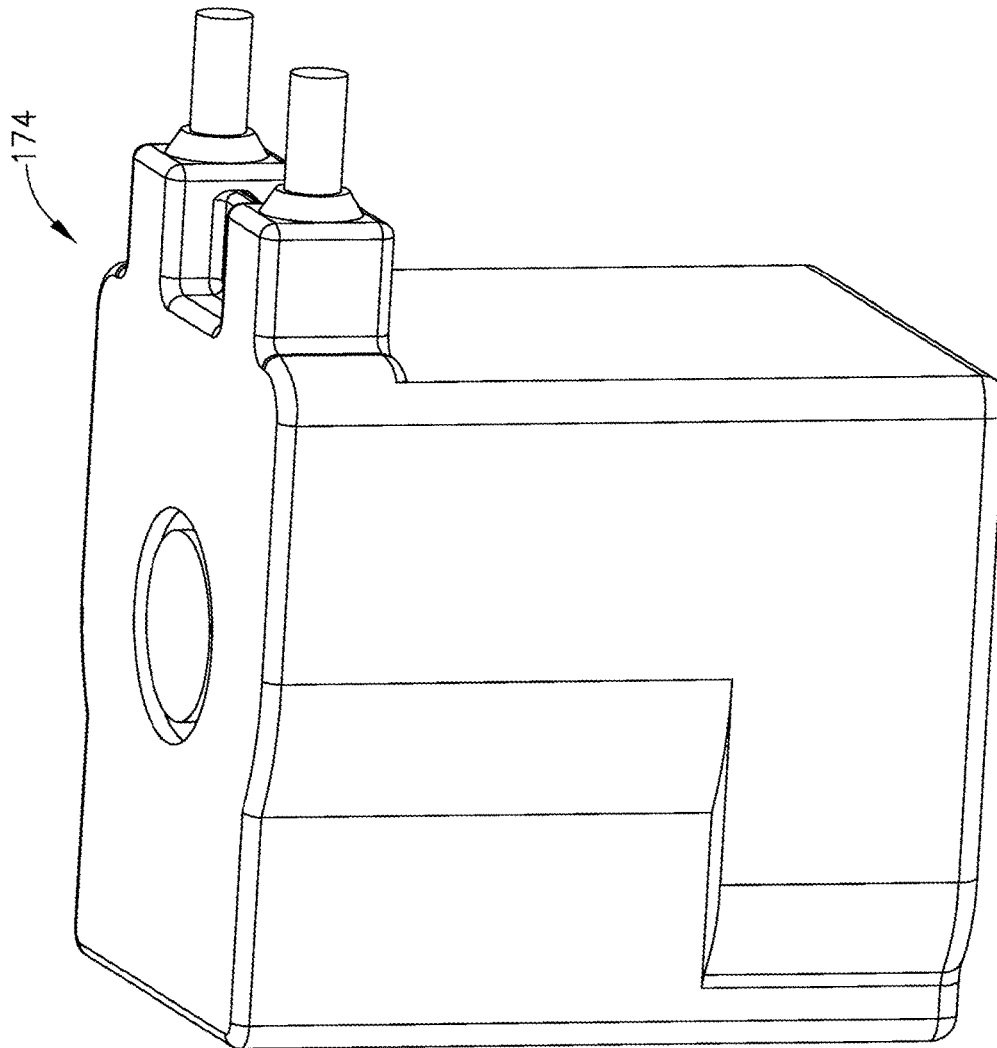


FIG. 7

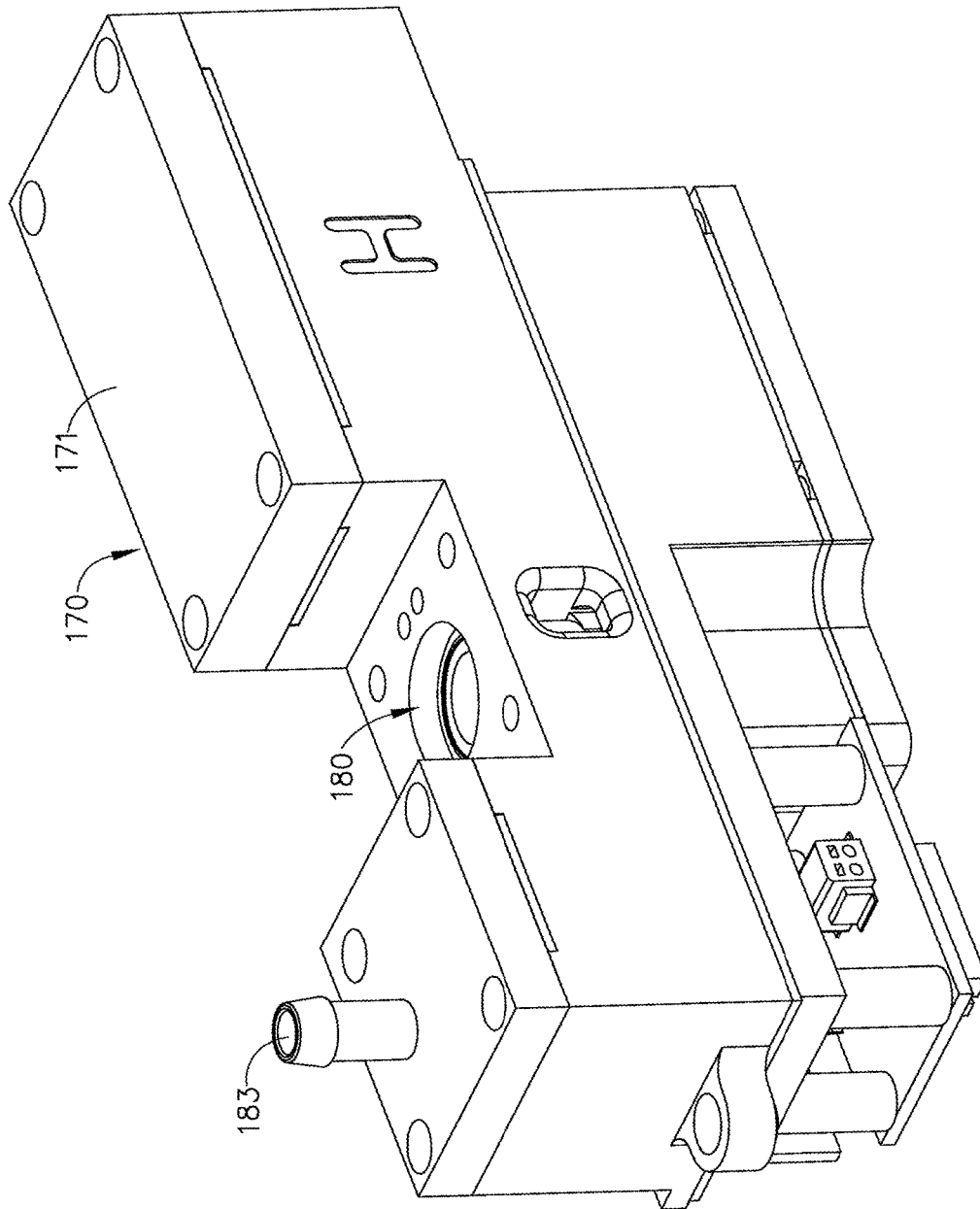


FIG. 8

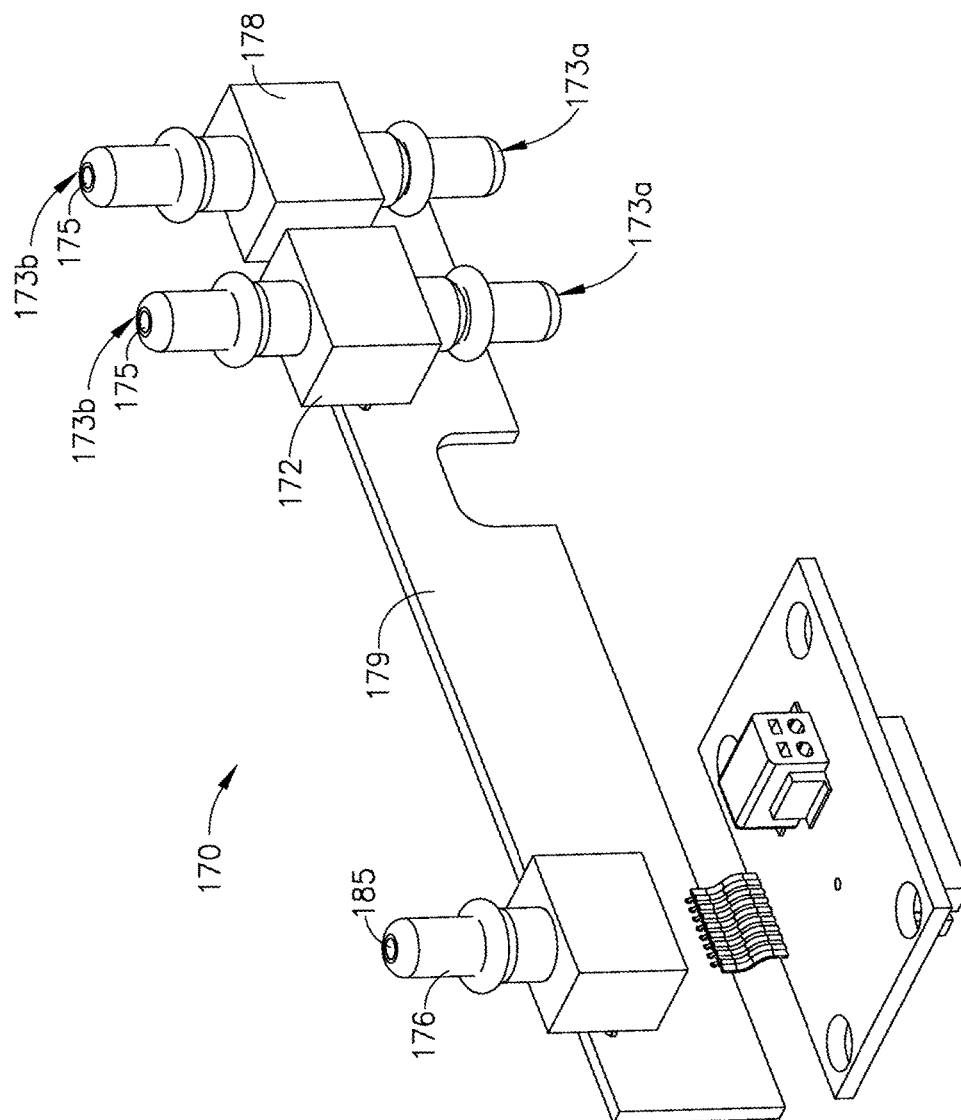


FIG. 9

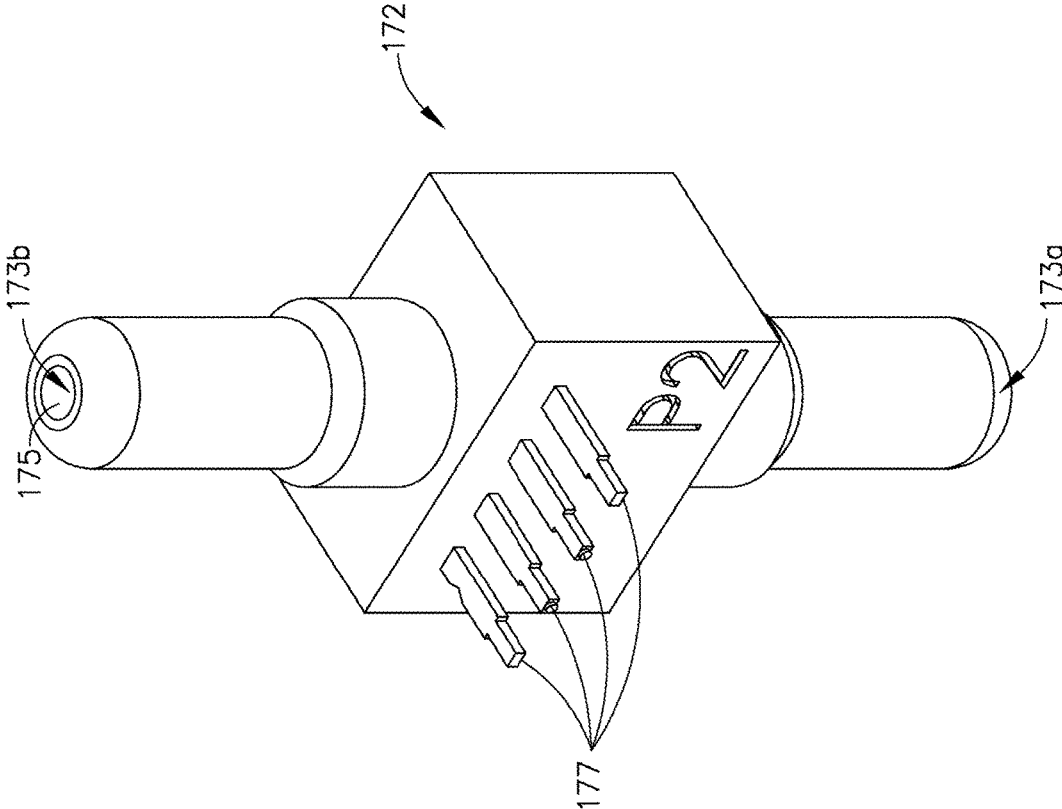


FIG. 10

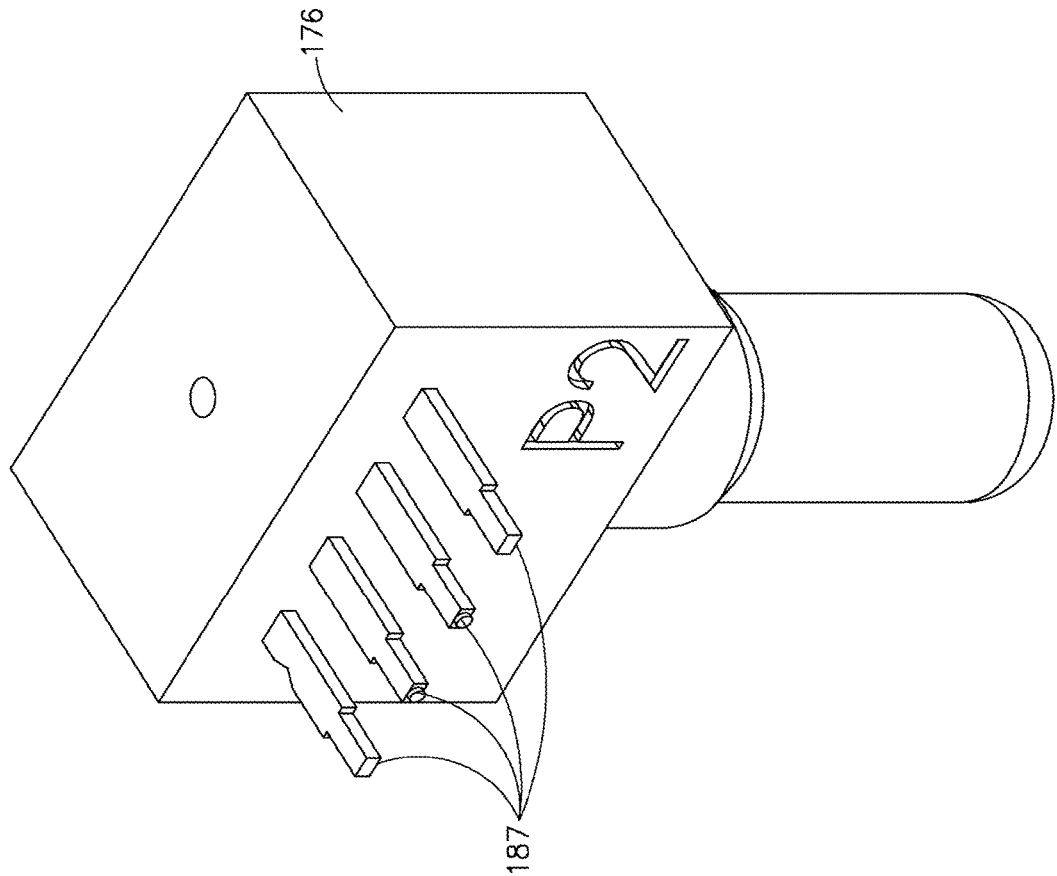


FIG. 11

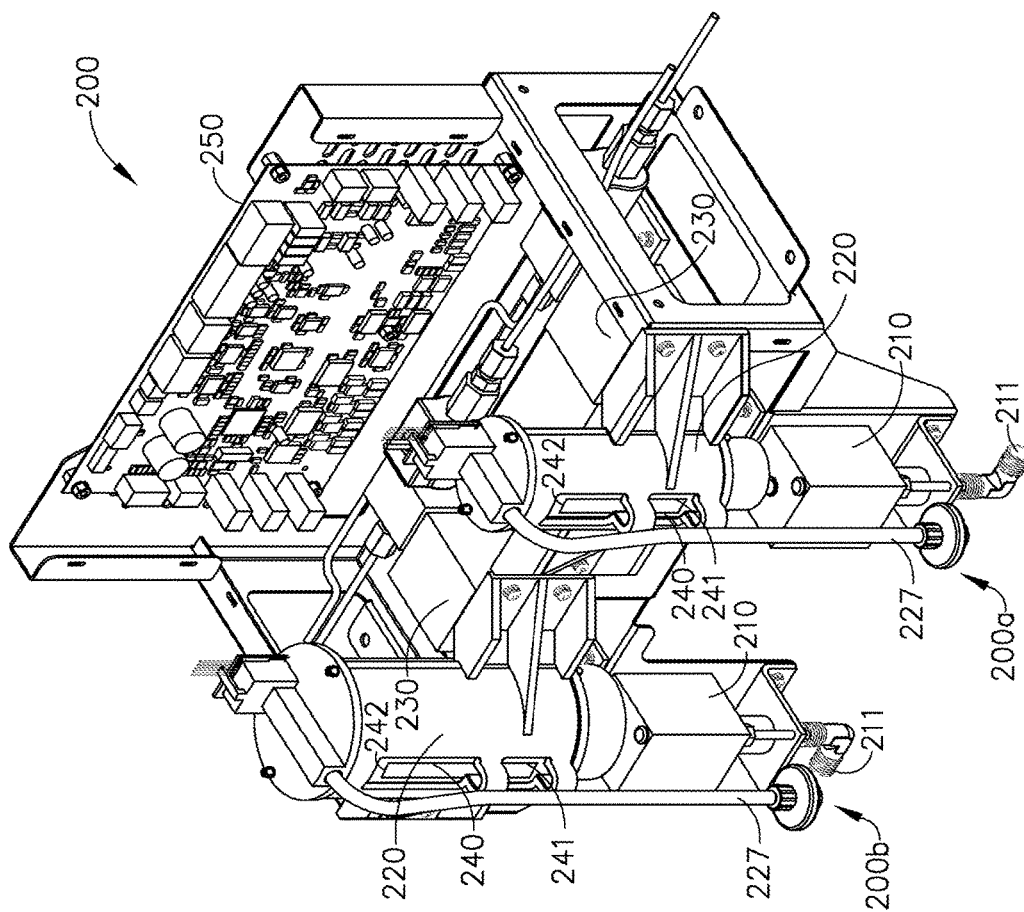


FIG. 12

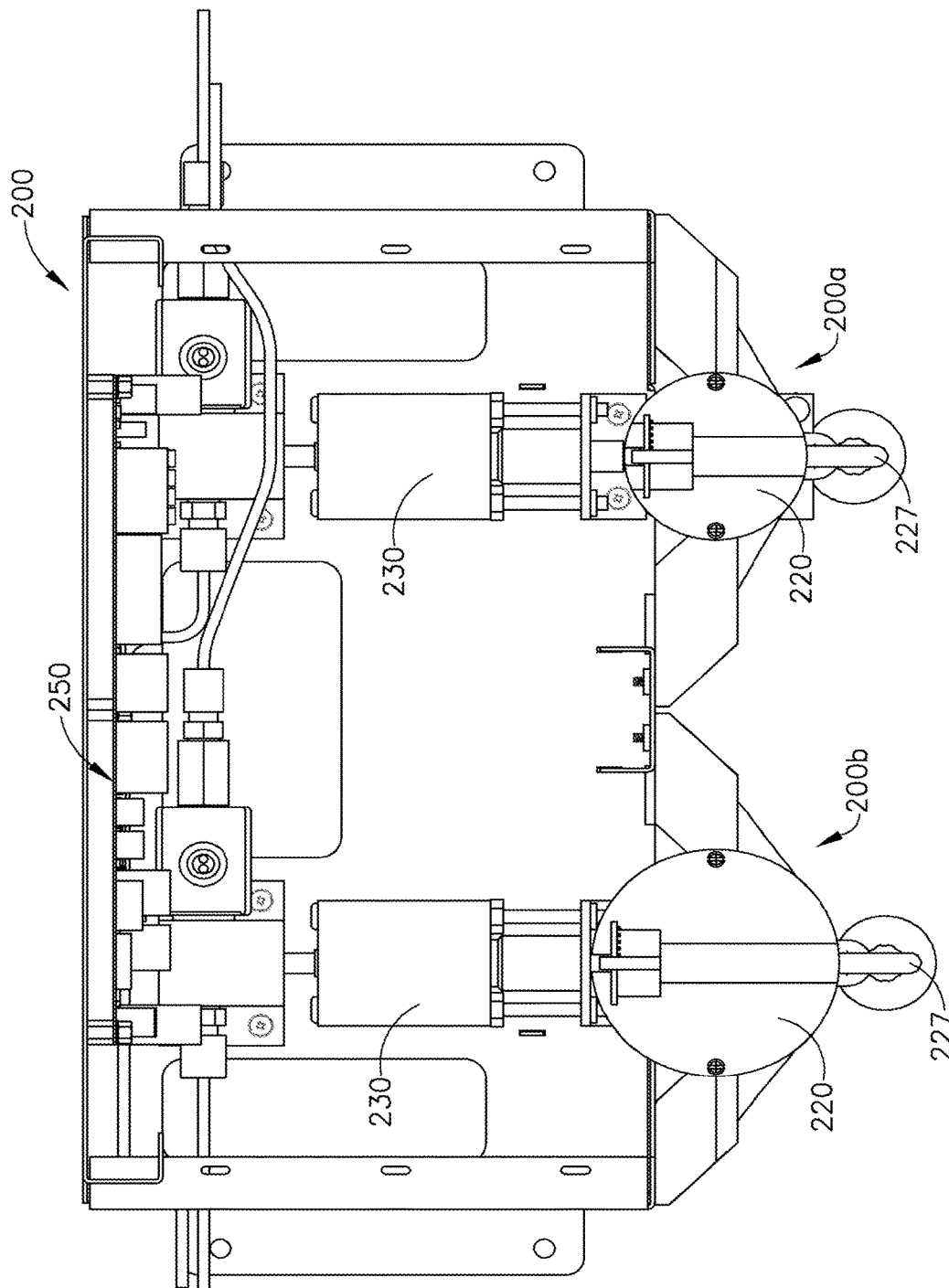


FIG. 13

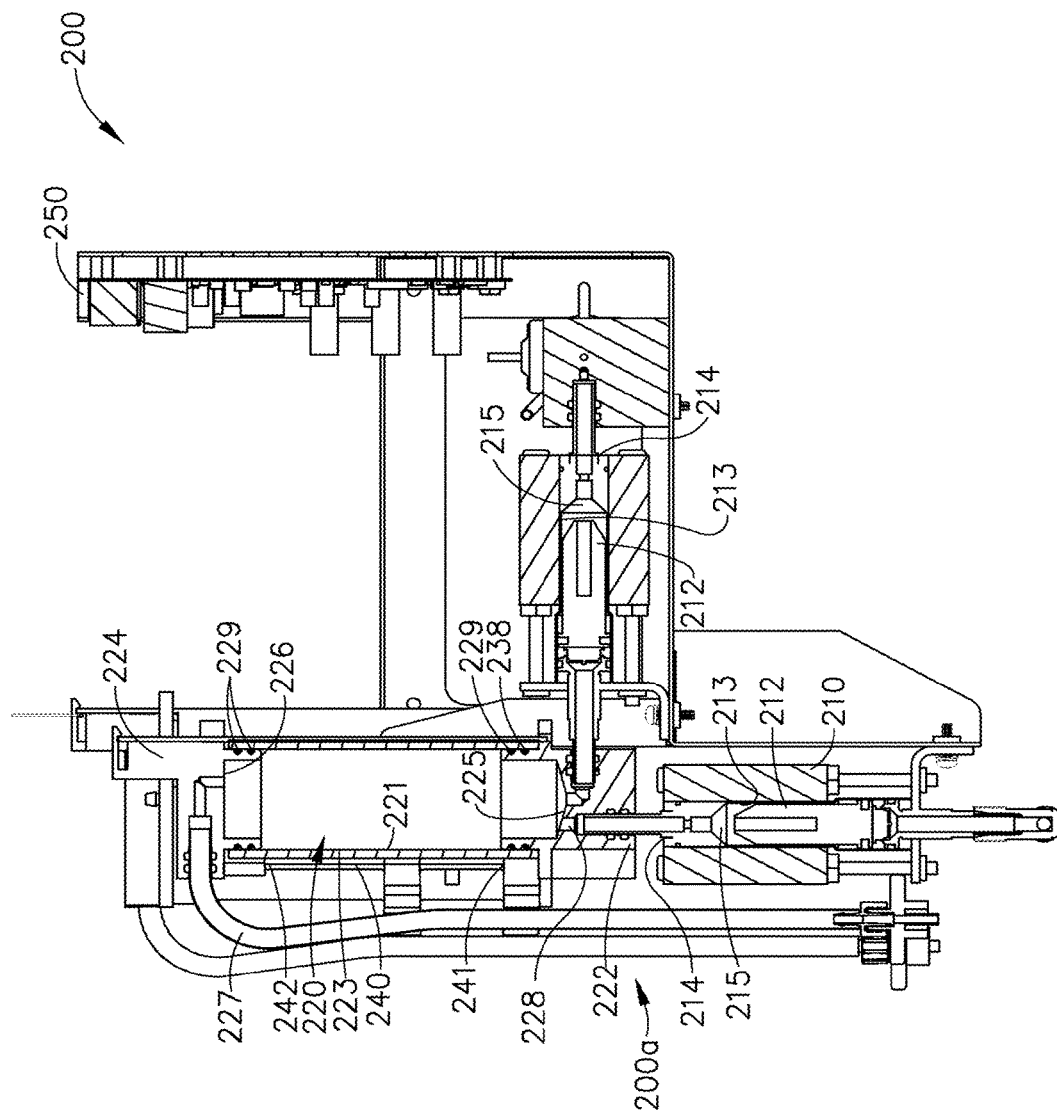


FIG. 14

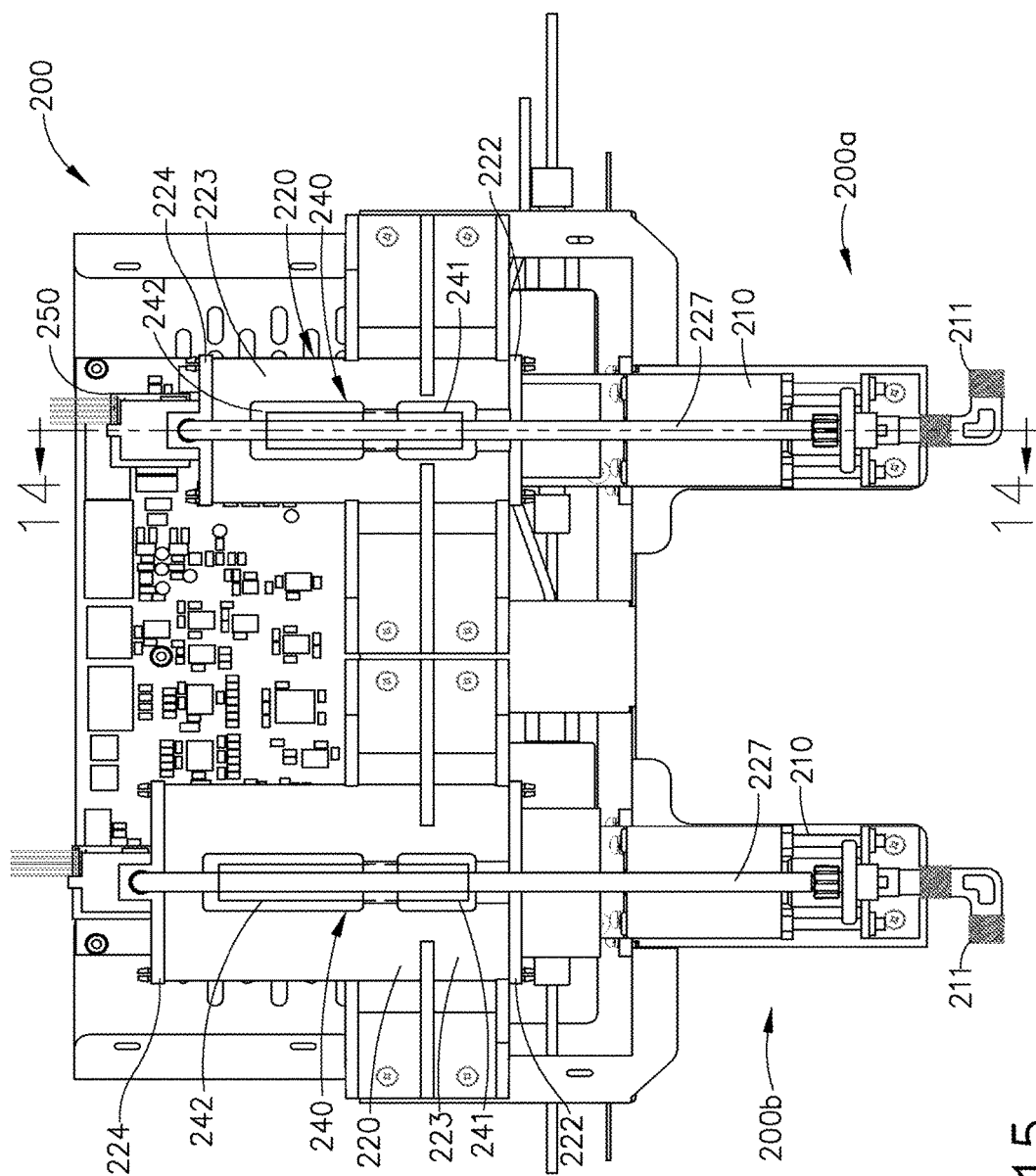


FIG. 15

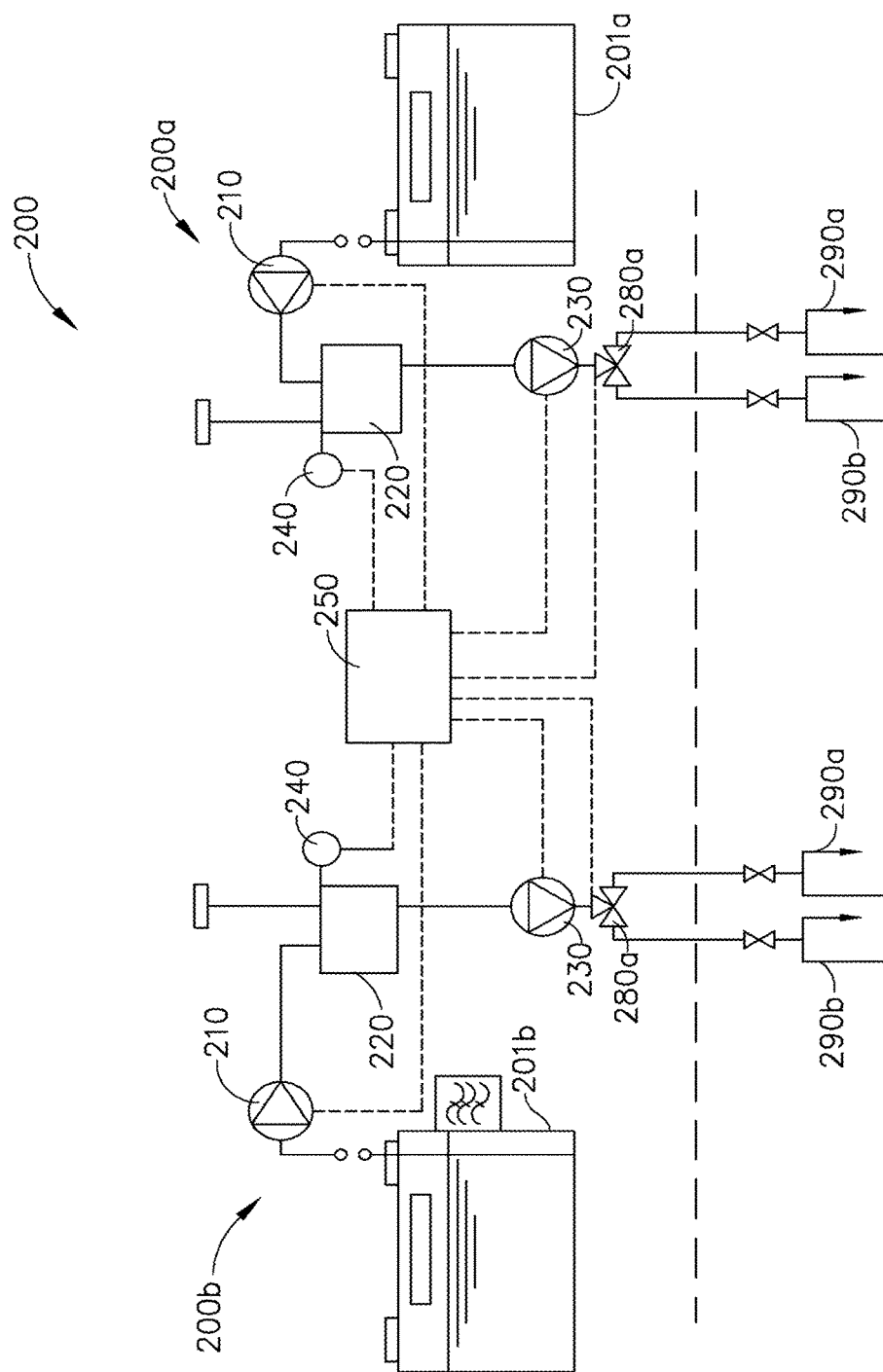


FIG. 16

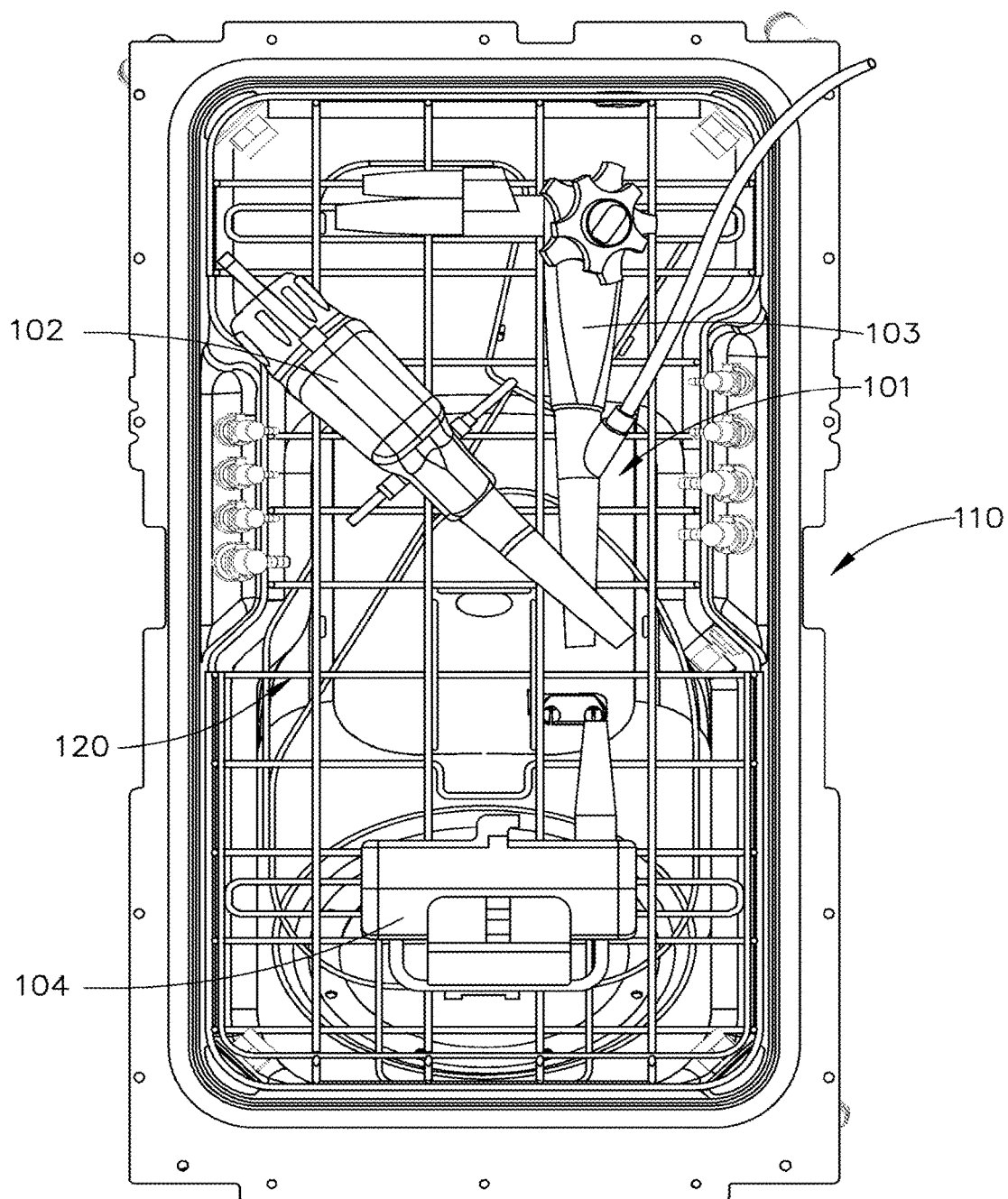


FIG. 17

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INSTRUMENT REPROCESSOR AND INSTRUMENT REPROCESSING METHODS

CROSS REFERENCE TO RELATED APPLICATIONS

The present application is a divisional application claiming priority under 35 U.S.C. § 120 to co-pending U.S. patent application Ser. No. 13/278,874, entitled "INSTRUMENT REPROCESSOR AND INSTRUMENT REPROCESSING METHODS," filed Oct. 21, 2011, the entire disclosure of which is incorporated by reference herein.

BACKGROUND

i. Field of the Invention

The present invention generally relates to the reprocessing, cleaning, sterilizing, and/or decontamination of medical instruments.

ii. Description of the Related Art

In various circumstances, an endoscope can include an elongate portion, or tube, having a distal end which can be configured to be inserted into the body of a patient and, in addition, a plurality of channels extending through the elongate portion which can be configured to direct water, air, and/or any other suitable fluid into a surgical site. In some circumstances, one or more channels in an endoscope can be configured to guide a surgical instrument into the surgical site. In any event, an endoscope can further include a proximal end having inlets in fluid communication with the channels and, in addition, a control head section having one or more valves, and/or switches, configured to control the flow of fluid through the channels. In at least one circumstance, an endoscope can include an air channel, a water channel, and one or more valves within the control head configured to control the flow of air and water through the channels.

Decontamination systems can be used to reprocess previously-used medical devices, such as endoscopes, for example, such that the medical devices can be used again. A variety of decontamination systems exist for reprocessing endoscopes. In general, such systems may include at least one rinsing basin in which an endoscope that is to be cleaned and/or disinfected can be placed. The rinsing basin is commonly supported by a housing that supports a circulation system of lines, pumps and valves for the purpose of directing a cleaning and/or disinfecting agent into and/or onto an endoscope which has been placed in the basin. During the decontamination process, the channels within the endoscope can be evaluated in order to verify that the channels are unobstructed. In various embodiments, the circulation system can be fluidly coupled to the endoscope channels by connectors which releasably engage ports which can define the ends of the channels. Such connectors can achieve a fluid-tight seal while attached to the endoscope, yet they can be easily releasable at the conclusion of the decontamination process.

The foregoing discussion should not be taken as a disavowal of claim scope.

SUMMARY

In at least one form, an instrument reprocessor for cleaning a medical instrument can comprise a chamber configured to receive the medical instrument, a supply of reprocessing fluid, a supply pump in fluid communication with the supply of reprocessing fluid, wherein the supply pump comprises a

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positive-displacement pump, and a reservoir in fluid communication with the supply pump, wherein the reservoir comprises a top and a bottom, and wherein the reservoir can comprise a reprocessing fluid height between the top and the bottom. The instrument reprocessor can further comprise a linear sensor extending between the reservoir top and the reservoir bottom, wherein the linear sensor is configured to detect the reprocessing fluid height and, in addition, a processor in signal communication with the linear sensor, wherein the processor is configured to operate the supply pump when the reprocessing fluid height is below a predetermined height, and wherein the predetermined height is between the reservoir top and the reservoir bottom. The instrument reprocessor can further comprise a dispensing pump in fluid communication with the reservoir bottom and the chamber, wherein the dispensing pump comprises a positive-displacement pump, and wherein the processor is configured to operate the dispensing pump.

In at least one form, a method of controlling the flow of reprocessing fluid through an instrument having at least a first channel and a second channel can comprise the steps of operating a pump in fluid communication with a reprocessing fluid source, flowing the reprocessing fluid through a first fluid circuit comprising a first valve and a first pressure differential sensor, wherein the first fluid circuit is in fluid communication with the pump and the first channel, and flowing the reprocessing fluid through a second fluid circuit comprising a second valve and a second pressure differential sensor, wherein the second fluid circuit is in fluid communication with the pump and the second channel. The method can further comprise the steps of detecting a first pressure differential in the reprocessing fluid flowing into the first valve utilizing the first pressure differential sensor, detecting a second pressure differential in the reprocessing fluid flowing into the second valve utilizing the second pressure differential sensor, modulating the first valve to control the first flow rate of reprocessing fluid through the first channel utilizing an output from the first pressure differential sensor, and modulating the second valve to control the second flow rate of reprocessing fluid through the second channel utilizing an output from the second pressure differential sensor.

In at least one form, an instrument reprocessor for cleaning a medical instrument including a passage can comprise a chamber configured to receive the medical instrument, a supply connector configured to be fluidly coupled with the passage, a pump configured to pressurize a reprocessing fluid and supply the reprocessing fluid to the supply connector, the pump comprising an inlet and an outlet, and a gauge pressure sensor positioned to sense the gauge pressure of the reprocessing fluid flowing from the pump outlet. The instrument reprocessor can further comprise a flow control system including a valve in fluid communication with the supply connector, wherein the valve is configured to control a flow rate of reprocessing fluid through the passage, and wherein the valve comprises an inlet and an outlet. The instrument reprocessor can further include a pressure differential sensor configured to sense a pressure drop in the reprocessing fluid on opposite sides of a fixed orifice, wherein the pressure differential sensor is positioned downstream with respect to the gauge pressure sensor and upstream with respect to the valve outlet, and a processor in signal communication with the pressure differential sensor, wherein the processor is configured to interpret the flow rate based on the pressure drop and command the valve to at least one of at least partially close and at least partially open.

In at least one form, a method of utilizing a monitoring system for maintaining a volume of reprocessing fluid

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within a supply reservoir for a fluid circulation system of an instrument reprocessor can comprise the steps of supplying a quantity of reprocessing fluid to the supply reservoir from a reprocessing fluid source, sensing the quantity of reprocessing fluid in the supply reservoir, and determining whether the quantity of reprocessing fluid in the supply reservoir is more than a predetermined amount. The method can further comprise the steps of operating a positive-displacement filling pump to supply reprocessing fluid to the supply reservoir if the quantity of reprocessing fluid in the supply reservoir is less than the predetermined amount, wherein the positive-displacement filling pump is configured to supply a fixed volume of reprocessing fluid per stroke, monitoring the quantity of reprocessing fluid in the supply reservoir as the positive-displacement filling pump is being operated, determining whether the quantity of reprocessing fluid in the supply reservoir has increased by a re-supply volume equal to the product of the volume displaced per stroke and the number of strokes of the positive-displacement filling pump, and broadcasting an alert if the quantity of reprocessing fluid in the supply reservoir has not increased by the re-supply volume.

In at least one form, a method of controlling the flow of reprocessing fluid through an instrument comprising a channel can comprise the steps of operating a pump in fluid communication with a reprocessing fluid source, measuring the gauge pressure of the reprocessing fluid flowing from the pump, adjusting the flow of the reprocessing fluid to adjust the gauge pressure of the reprocessing fluid, and flowing the reprocessing fluid through a fluid circuit comprising a valve and a pressure differential sensor, wherein the fluid circuit is in fluid communication with the pump and the channel. The method can further comprise the steps of detecting a pressure differential in the reprocessing fluid flowing into the valve utilizing the pressure differential sensor, and modulating the valve to control the flow rate of reprocessing fluid through the channel utilizing an output from the pressure differential sensor.

In at least one form, a method of controlling the flow of reprocessing fluid through an instrument having at least a first channel and a second channel, wherein the first channel is defined by a first value of a parameter and the second channel is defined by a second value of the parameter, can comprise the steps of initializing a pump in fluid communication with a reprocessing fluid source to begin an operating cycle, supplying the reprocessing fluid to a first fluid circuit comprising a first valve, wherein the first fluid circuit is in fluid communication with the pump and the first channel, and supplying the reprocessing fluid to a second fluid circuit comprising a second valve, wherein the second fluid circuit is in fluid communication with the pump and the second channel. The method can further comprise the step of modulating the first valve to limit the flow of reprocessing fluid through the first channel, wherein the flow of reprocessing fluid is limited by an amount based on the difference between the first value of the parameter and the second value of the parameter, whereby the reprocessing fluid flows through the first channel and the second channel when the pump is initialized.

The foregoing discussion should not be taken as a disavowal of claim scope.

DESCRIPTION OF THE DRAWINGS

The features and advantages of this invention, and the manner of attaining them, will become more apparent and the invention itself will be better understood by reference to

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the following description of embodiments of the invention taken in conjunction with the accompanying drawings, wherein:

FIG. 1 is a perspective view of an endoscope reprocessor in accordance with at least one embodiment comprising two basins;

FIG. 2 is a perspective view of the basins of the endoscope reprocessor of FIG. 1;

FIG. 3 is a diagram of a channel flow subsystem of the endoscope reprocessor of FIG. 1;

FIG. 3A is a diagram of a channel flow subsystem for controlling the pressure of the fluid flowing therethrough;

FIG. 4 is a perspective view of a manifold assembly including a plurality of flow control units;

FIG. 5 is a perspective view of the manifold of the manifold assembly of FIG. 4;

FIG. 6 is a perspective view of a flow control unit configured to control the flow of fluid through an endoscope channel supply line;

FIG. 7 is a perspective view of a proportional valve of the flow control unit of FIG. 6;

FIG. 8 is a perspective view of the flow control unit of FIG. 6 with the proportional valve of FIG. 7 removed;

FIG. 9 is a perspective view of a subassembly of the control unit of FIG. 6 including a printed circuit board (PCB) assembly, a gauge pressure sensor, and two differential pressure sensors;

FIG. 10 is a perspective view of the differential pressure sensor of the control unit of FIG. 9.

FIG. 11 is a perspective view of the gauge pressure sensor of the control unit of FIG. 9;

FIG. 12 is a perspective view of a fluid delivery system;

FIG. 13 is a top view of the fluid delivery system of FIG. 12;

FIG. 14 is a cross-sectional elevational view of the fluid delivery system of FIG. 12;

FIG. 15 is an elevational view of the fluid delivery system of FIG. 12;

FIG. 16 is a schematic of the fluid delivery system of FIG. 12; and

FIG. 17 illustrates an endoscope positioned within an endoscope carrier in the basin of FIG. 2.

Corresponding reference characters indicate corresponding parts throughout the several views. The exemplifications set out herein illustrate certain embodiments of the invention, in one form, and such exemplifications are not to be construed as limiting the scope of the invention in any manner.

DETAILED DESCRIPTION

Certain exemplary embodiments will now be described to provide an overall understanding of the principles of the structure, function, manufacture, and use of the devices and methods disclosed herein. One or more examples of these embodiments are illustrated in the accompanying drawings. Those of ordinary skill in the art will understand that the devices and methods specifically described herein and illustrated in the accompanying drawings are non-limiting exemplary embodiments and that the scope of the various embodiments of the present invention is defined solely by the claims. The features illustrated or described in connection with one exemplary embodiment may be combined with the features of other embodiments. Such modifications and variations are intended to be included within the scope of the present invention.

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Reference throughout the specification to “various embodiments,” “some embodiments,” “one embodiment,” or “an embodiment,” or the like, means that a particular feature, structure, or characteristic described in connection with the embodiment is included in at least one embodiment. Thus, appearances of the phrases “in various embodiments,” “in some embodiments,” “in one embodiment,” or “in an embodiment,” or the like, in places throughout the specification are not necessarily all referring to the same embodiment. Furthermore, the particular features, structures, or characteristics may be combined in any suitable manner in one or more embodiments. Thus, the particular features, structures, or characteristics illustrated or described in connection with one embodiment may be combined, in whole or in part, with the features structures, or characteristics of one or more other embodiments without limitation. Such modifications and variations are intended to be included within the scope of the present invention.

The terms “proximal” and “distal” are used herein with reference to a surgical instrument. The term “proximal” referring to the portion closest to the clinician and the term “distal” referring to the portion located away from the clinician. It will be further appreciated that, for convenience and clarity, spatial terms such as “vertical,” “horizontal,” “up,” and “down” may be used herein with respect to the drawings. However, in some circumstances, the devices disclosed herein may be used in many orientations and positions, and these terms are not intended to be limiting and/or absolute.

As described above, referring to FIG. 1, a medical instrument reprocessor, such as endoscope reprocessor 100, for example, can be configured to clean one or more endoscopes. In certain embodiments, the endoscope reprocessor can be configured to disinfect and/or sterilize an endoscope. In various embodiments, the endoscope reprocessor can comprise at least one basin 110, wherein each basin 110 can be configured to receive an endoscope therein. Although the endoscope reprocessor 100 comprises two basins, for example, various alternative embodiments are envisioned which comprise any suitable number of basins 110. In various embodiments, the reprocessor 100 can further include one or more endoscope carriers 120 configured to support an endoscope therein which can be placed in each basin 110. In use, a clinician can place the endoscope into the endoscope carrier 120 and then position the endoscope carrier 120 within the basin 110. Alternatively, the clinician can position the carrier 120 in the basin 110 and then position the endoscope in the carrier 120. In either event, once the endoscope has been suitably positioned within the basin 110, a folding door 130 can be closed, secured and/or sealed to the reprocessor frame 140 in order to enclose the endoscope within the basin 110. Thereafter, the clinician can operate the endoscope reprocessor 100 by interfacing with a control panel 150, for example. Exemplary embodiments of the basin 110, the carrier 120, and the folding door 130 are described in a contemporaneously-filed, co-owned U.S. Patent Application entitled INSTRUMENT REPROCESSORS, SYSTEMS, AND METHODS, U.S. patent application Ser. No. 13/278,837, the entire disclosure of which is incorporated by reference herein. Referring now to FIG. 17, an endoscope 101 is illustrated as being positioned within a carrier 120 which is positioned in a basin 110. In various embodiments, the endoscope 101 can comprise various portions 102, 103, and/or 104 which can be supported within the carrier 120.

In various embodiments, further to the above, the endoscope reprocessor 100 can include a circulation system

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which can circulate one or more reprocessing fluids such as detergent, sterilant, disinfectant, water, alcohol, and/or any other suitable fluid, for example, through the endoscope and/or spray the fluid onto the endoscope. The circulation system can comprise a fluid supply and a circulation pump, wherein the circulation pump can be fluidly connected to the fluid supply such that the fluid can be drawn from the fluid supply into the circulation system. In certain embodiments, the circulation system can include a mixing chamber in which the fluid can be mixed with another fluid, such as water, for example, wherein the mixing chamber can be in fluid communication with the circulation pump. In either event, referring now to FIG. 2, each basin 110 can comprise one or more spray nozzles 112 which can be in fluid communication with the circulation pump such that the fluid pressurized by the circulation pump can be ejected from the circulation system through the nozzles 112 and onto the endoscope. In at least one such embodiment, each basin 110 can include a plurality of nozzles 112 positioned around the perimeter thereof and one or more nozzles 112 which can spray upwardly from the basin floor, or backsplash, 111. Certain exemplary embodiments are described in greater detail in a contemporaneously-filed, co-owned U.S. Patent Application entitled INSTRUMENT REPROCESSORS, SYSTEMS, AND METHODS, U.S. patent application Ser. No. 13/278,837, the entire disclosure of which is incorporated by reference herein.

In various embodiments, further to the above, each basin 110 can be configured to guide the fluid sprayed therein downwardly toward a drain 116 positioned at the bottom thereof wherein the fluid can then re-enter the circulation system. In order to clean, disinfect, and/or sterilize internal channels within the endoscope, the endoscope reprocessor 100 can include one or more supply lines in fluid communication with the circulation system pump which can be placed in fluid communication with the internal channels of the endoscope. In various embodiments, referring again to FIG. 2, each basin 110 can include one or more ports 114 which can comprise the ends of the supply lines. In the illustrated embodiment, each basin 110 has a bank of four ports 114 positioned on opposite sides thereof, although other alternative embodiments are envisioned which can comprise any suitable number and arrangement of ports 114. In certain embodiments, the endoscope reprocessor 110 can further comprise one or more flexible conduits which can be connected and/or sealingly engaged with the ports 114 and the channels defined in the endoscope such that the pressurized fluid from the circulation system can flow through the ports 114, the flexible conduits, and then into the endoscope. Flexible conduits and the connectors used to sealingly engage the flexible conduits to the endoscope are described in U.S. patent application Ser. No. 12/998,459, entitled FLUID CONNECTOR FOR ENDOSCOPE REPROCESSING SYSTEM, which was filed on Aug. 29, 2011 and U.S. patent application Ser. No. 12/998,458, entitled QUICK DISCONNECT FLUID CONNECTOR, which was also filed on Aug. 29, 2011, the entire disclosures of which are incorporated by reference herein.

In various circumstances, further to the above, the channels defined within the endoscope can become blocked or obstructed by debris, for example, which can inhibit the endoscope from being properly cleaned, disinfected, and/or sterilized. In some circumstances, the debris positioned within an endoscope channel can at least partially block the flow of the fluid therethrough thereby reducing the rate in which the fluid can flow through the channel. Various embodiments of an endoscope reprocessor are envisioned

herein in which the flow rate of the fluid through an endoscope channel can be monitored to evaluate whether an obstruction exists in the channel. In such embodiments, the monitoring system could measure the actual flow rate of the fluid and compare it to flow rate of the fluid which would be expected given the pressure in which the fluid was pressurized to by the circulation pump. Certain monitoring systems could also evaluate whether the connectors of the flexible conduit are sealingly engaged with the endoscope channel and/or the basin ports **114**, for example. In such systems, the monitoring system could detect whether the flow rate of the fluid is above an expected flow rate, for example. The entire disclosure of U.S. Pat. No. 7,879,289, entitled **AUTOMATED ENDOSCOPE REPROCESSOR SELF-DISINFECTION CONNECTION**, which issued on Feb. 1, 2011, is incorporated by reference herein.

Referring now to the diagram of FIG. 3, an endoscope reprocessor can comprise a channel flow subsystem **160** including a manifold **166** in fluid communication with the circulation system pump, indicated as pump **162**, which can be configured to distribute the pressurized fluid to the channel supply lines of the endoscope reprocessor and then to the channels of the endoscope. Such channel supply lines of the endoscope reprocessor are indicated as supply lines **164** in the diagram of FIG. 3. In various embodiments, each endoscope reprocessor supply line **164** can include at least one differential pressure sensor **172**, at least one proportional valve **174**, and at least one gauge pressure sensor **176**. In certain embodiments, referring now to FIGS. 6 and 9, each reprocessor channel supply line **164** can include a control unit assembly **170** comprising a housing **171**, a differential pressure sensor **172**, a proportional valve **174**, and a gauge pressure sensor **176**. In at least one such embodiment, each housing **171** can include an inlet **168** and an internal passage which can be configured to direct the flow of fluid through an inlet **173a** and then an outlet **173b** of the differential pressure sensor **172**. Between the inlet **173a** and the outlet **173b** of the differential pressure sensor **172** an orifice **175** (FIG. 10) can be defined which comprises a fixed diameter. In at least one such embodiment, the diameter of the orifice **175** can be constant along the length thereof. Such an orifice could be created by a drilling process, for example. In various other embodiments, the diameter of the orifice **175** may not be constant along the length thereof. In either circumstance, such orifices can be fixed in the sense that they do not change, or at least substantially change, over time. As described in greater detail below, referring now to FIGS. 9 and 10, the differential pressure sensor **172** can further comprise a plurality of electrical contacts **177** which can place the differential pressure sensor **172** in signal communication with a printed circuit board (PCB) assembly **179** of the control unit assembly **170**. The electrical contacts **177** can also be configured to supply the differential pressure sensor **172** with electrical power. Various pressure differential sensors are commercially available from Honeywell, for example.

As outlined above, the differential pressure sensor **172** can be in electrical and/or signal communication with the PCB assembly **179**. More specifically, the PCB assembly **179** can include, among other things, a microprocessor and/or any suitable computer, for example, wherein the differential pressure sensor **172** can be configured to generate a voltage potential which is communicated to the microprocessor of the PCB assembly **179**. In at least one such embodiment, the microprocessor of the PCB assembly **179** can be configured to interpret the voltage potential supplied by the differential

pressure sensor **172** and calculate the flow rate of the fluid flowing through the differential pressure sensor **172**.

In certain embodiments, further to the above, a plurality of fluid flow rate values can be stored in a look-up table defined within programmable memory on the PCB assembly **179**, for example. Oftentimes, in various embodiments, the values of the expected fluid flow rates in the look-up table can be theoretically predicted while, in certain embodiments, the values can be empirically tested and then stored in the programmable memory. In either event, the fluid flow rate can be determined as a function of the gauge pressure of the fluid being discharged by the circulation pump **162** and supplied to the manifold **166**. In at least one such embodiment, a gauge pressure sensor, such as gauge pressure sensor **159** (FIG. 3), for example, can be positioned downstream with respect to the outlet of the circulation pump **162** such that the gauge pressure of the fluid being supplied to each of the reprocessor channel supply lines **164** can be measured. In such embodiments, the gauge pressure sensor **159** can be placed in electrical and/or signal communication with each PCB assembly **179** of the flow control units **170** such that the gauge pressure of the fluid can be communicated to the microprocessor of each PCB assembly **179** in the form of a voltage potential. Once the gauge pressure of the fluid has been communicated to the PCB assembly **179**, in various embodiments, the microprocessor can derive the fluid flow rate of the fluid from the look-up table and compare the fluid flow rate value to the target fluid flow rate. Oftentimes, the actual flow rate will not exactly match the target flow rate and, thus, a range of values for the actual flow rate between a minimum target value and a maximum target value may be acceptable.

In various embodiments, further to the above, the fluid flow rate through an reprocessor channel supply line **164** can be determined as a function of two variables, the gauge pressure reading from the gauge pressure sensor **159**, as described above, and, in addition, the pressure differential reading from the differential pressure sensor **172** of a corresponding flow control unit **170**. Such a system may utilize a plurality of look-up tables to derive the flow rate of the fluid. For instance, for every potential gauge pressure of the fluid that may be supplied to the manifold **166**, such as 35 psi, for example, a table correlating the reading of the differential pressure sensor **172** and the expected flow rate could be stored within each PCB assembly **179**. In such embodiments, a large range of gauge pressures may need to be accounted for and, thus, a large number of look-up tables may be needed. In various other embodiments, the pressure of the fluid being supplied to the reprocessor supply lines **164** may be limited to a particular pressure or a limited range of pressures. In at least one such embodiment, referring to FIG. 3A, the fluid circulation system of the instrument reprocessor **100** can include a pressure limiting valve, such as a proportional valve **158**, for example, which can be in fluid communication with the outlet of the circulation pump **162** and a fluid feedback loop **157**. In at least one such embodiment, the proportional valve **158** can be configured to redirect a portion the fluid being discharged by the pump **162** and return the redirected fluid to the circulation system at an inlet positioned upstream with respect to the pump **162**, for example, such that the pressure of the fluid being supplied to the manifold **166** is provided at a constant, or an at least substantially constant pressure, such as 35 psig, for example. In at least one such embodiment, a PCB assembly including a microprocessor and/or any suitable computer, for example, can be utilized which is in electrical and/or signal communication with the gauge pressure sensor **159**

and the proportional valve **158**. In use, when the gauge pressure of the fluid is above 35 psig, for example, the PCB assembly can command the proportional valve **158** to open a certain amount, or an additional amount, to permit fluid, or more fluid, to flow through the fluid feedback loop **157**. In such circumstances, such actions may lower the pressure of the fluid flowing to the manifold **166**. In the event that the pressure of the fluid remains greater than 35 psig, the PCB assembly could command the proportional valve **158** to open an additional amount. Such steps could be repeated any suitable number of times to arrive at the desired pressure of the fluid. Correspondingly, when the gauge pressure of the fluid is below 35 psig, for example, the PCB assembly can command the proportional valve **158** to close a certain amount to reduce the rate of fluid flowing through the fluid feedback loop **157**. In such circumstances, such actions may raise the pressure of the fluid flowing to the manifold **166**. In the event that the pressure of the fluid remains lower than 35 psig, the PCB assembly could command the proportional valve **158** to close an additional amount. Such steps could be repeated any suitable number of times to arrive at the desired pressure of the fluid.

In view of the above, in various embodiments, the gauge pressure of the fluid being supplied to the flow control units **170** of the reprocessor supply lines **164** can be controlled such that it is maintained at a constant, or an at least substantially constant, pressure. Accordingly, one of the variables for calculating the flow rate of the fluid flowing through the reprocessor supply lines **164** can be held constant, or at least substantially constant. Thus, as a result, the flow rate of the fluid through each reprocessor supply line **164** and its associated control unit **170** may be a function of only one variable, i.e., the reading from the differential pressure sensor **172**. In at least one such embodiment, only one look-up table may be needed to calculate the actual, calculated flow rate and/or correlate the actual, calculated flow rate with the target flow rate to determine whether the actual, calculated flow rate is between minimum and maximum acceptable values for the fluid flow rate through a reprocessor supply line **164**.

In the event that the actual fluid flow rate is between minimum and maximum acceptable values for a given endoscope channel, as supplied thereto by a reprocessor supply line **164**, the PCB assembly **179** of the corresponding flow control unit **170** may not adjust the proportional valve **174** and, instead, may continue to monitor the flow rate of the fluid flowing through the flow control unit **170**. In the event that the actual flow rate of the fluid through the reprocessor supply line **164** is below the minimum acceptable value or above the maximum acceptable value stored in the look-up table for a given gauge pressure for a given reprocessor supply line **164**, the PCB assembly **179** may open, partially open, close, and/or partially close the proportional valve **174** associated therewith. In at least one embodiment, referring to FIGS. 6-8, the proportional valve **174** can comprise an orifice or chamber **180**, a valve element positioned within the chamber **180**, and a solenoid which can be activated to rotate the element within the chamber **180** between an open position in which fluid can flow through the chamber, a closed position in which the element obstructs the flow of fluid therethrough, and/or any other suitable position inbetween.

In various embodiments, further to the above, the microprocessor of the PCB assembly **179** can be configured to adjust the position of the valve element within the valve chamber **180** of the proportional valve **174**. In use, if the actual fluid flow rate through an reprocessor supply line **164**

is higher than the target fluid flow rate, the solenoid of the proportional valve **174** can move the valve element toward its closed position to further constrict the flow of fluid therethrough. Likewise, if the actual fluid flow rate through the reprocessor supply line **164** is lower than the target fluid flow rate, the solenoid of the proportional valve **174** can move the valve element toward its open position to reduce the constriction to the fluid flowing therethrough. In various embodiments, the valve element can be rotated from an open position to a first position to constrict a valve orifice a first amount, such as approximately 25%, for example, to a second position to constrict the valve orifice a second amount, such as approximately 50%, for example, to a third position to constrict the valve orifice a third amount, such as approximately 75%, for example, and to a closed position in which the valve orifice is approximately 100% constricted, for example. In various embodiments, the valve element of the proportional valve **174** can be positionable in any suitable number of positions to provide a desired constriction to the flow of fluid through the valve **174**. In any event, the position of the valve element can be controlled by a voltage potential applied to the valve solenoid by the PCB assembly **179** wherein, for example, a lower voltage potential applied to the valve solenoid can result in the valve element being oriented in a position which is closer to its fully-closed position as compared to when a higher voltage potential is applied to the valve solenoid which orients the valve element in a position which is closer to its fully-open position, for example.

In various circumstances, as a result of the above, the PCB assembly **179** can be configured to continuously monitor the flow rate of the fluid flowing through a reprocessor supply line **164** and adjust the proportional valve **174** to increase and/or reduce the rate of fluid flowing through the reprocessor supply line **164** and, correspondingly, the endoscope channel fluidly coupled thereto. In various embodiments, further to the above, the PCB assembly **179** can be configured to keep the flow rate of the fluid at and/or near a desired flow rate. In embodiments where the fluid being circulated is a sterilant or a solution including a sterilant, for example, the sterilant can sterilize the endoscope; however, the sterilant may also negatively affect or degrade the endoscope. Thus, in view of the above, the channel flow subsystem **160** can be configured to supply a sufficient minimum flow of sterilant to the endoscope in order to sterilize the endoscope yet limit the maximum flow of sterilant to the endoscope such that the sterilant does not overly degrade the endoscope. Similarly, in view of the above, the channel flow subsystem **160** can be configured to supply a sufficient minimum flow of disinfectant to the endoscope in order to disinfect the endoscope yet limit the maximum flow of disinfectant to the endoscope such that the disinfectant does not overly degrade the endoscope. In various embodiments, each endoscope channel supply line can further include a second differential pressure sensor, such as differential pressure sensor **178**, for example, which can also detect the flow rate of the fluid through the reprocessor supply line **164**. In at least one such embodiment, the first differential pressure sensor **172** and the second differential pressure sensor **178** of a control unit assembly **170** can be placed in parallel with one another wherein, in the event that the pressure sensors **172** and **178** supply appreciably different voltage readings to the PCB assembly **179**, the PCB assembly **179** can execute a corrective action routine which could include closing the proportioning valve **174**, for example, and/or issuing an alert or warning to the operator that the control unit assembly **170** may need to be serviced.

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As outlined above, each proportional valve **174** can be configured to control the condition of a variable orifice. In at least one such embodiment, each proportional valve **174** can comprise a biasing element, such as a spring, for example, which can be configured to bias the valve element of the proportional valve **174**, discussed above, into a normally-closed condition. The solenoid of the proportional valve **174**, as also discussed above, can be actuated to move the valve element into an at least partially open position. In at least one embodiment, a series of voltage pulses can be applied to the solenoid from the corresponding PCB assembly **179** which can control the degree, or amount, in which the valve element is opened. In at least one such embodiment, the greater frequency in which the voltage pulses are applied to the solenoid, the larger the variable orifice can be thereby permitting a larger flow rate of fluid therethrough. Correspondingly, the lower frequency in which the voltage pulses are applied to the solenoid, the smaller the variable orifice can be thereby permitting a smaller flow rate of fluid therethrough. If the voltage pulses are no longer applied to the solenoid of the proportional valve **174**, the biasing element can move the valve element into a closed condition once again. Other various embodiments are envisioned in which the valve element is biased into a normally-open condition and the solenoid of the proportional valve can act to bias the valve element into an at least partially closed condition. In various other embodiments, a valve for controlling the orifice can be configured to cycle a valve element between a fully open position and a fully closed position and control the rate of fluid flowing therethrough by controlling the time in which the valve element is closed as compared to the time in which the valve element is open. In at least one such embodiment, the valve element can be cycled rapidly between its open and closed conditions by a solenoid, for example.

Further to the above, each reprocessor supply line **164** can include a control unit assembly **170** wherein the control unit assemblies **170** can be configured to control the flow of fluid through the reprocessor supply lines **164** independently of another. In various embodiments, the control unit assemblies **170** may not be in electrical and/or signal communication with each other. In such embodiments, each control unit assembly **170** is configured to monitor and adjust the flow rate of the fluid flowing through a reprocessor supply line **164** without communicating with the other control unit assemblies **170**. In various other embodiments, however, the control unit assemblies **170** can be in electrical and/or signal communication with each other such that certain parameters of the fluid within the reprocessor supply lines **164** could be compared to one another, for example. In either event, the PCB assembly **179** of a control unit **170** can be programmed to fully open the proportional valve **174** thereof in the event that the gauge pressure exiting the control unit **170** exceeds a predetermined maximum pressure, such as approximately 21.75 psig, for example. In various embodiments, the gauge pressure sensor **176** of a control unit assembly **170**, mentioned above, can be configured to, one, detect the gauge pressure of the fluid exiting the proportional valve **174** of a reprocessor supply line **164** and, two, communicate a voltage potential to its respective PCB assembly **179** which can interpret the voltage potential into a gauge pressure. As compared to the differential pressure sensors **172** and **178** which can detect a pressure drop in the fluid between two points in a fluid supply line, the gauge pressure sensors **176** can detect the actual pressure of the fluid, or gauge pressure. In various embodiments, referring to FIGS. 9 and 11, a gauge pressure sensor **176** can comprise a passage **185**

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which can be configured to direct the flow of fluid past a sensing element and to an outlet **183** of the flow control unit **170**. Similar to the above, each gauge pressure sensor **176** can comprise a plurality of electrical contacts **187** which can place the gauge pressure sensor **176** in electrical and/or signal communication with its corresponding PCB assembly **179**.

Further to the above, the manifold **166** of the fluid circulation system **160** can be configured to distribute the fluid flowing therethrough to eight endoscope reprocessor supply lines **164** and the endoscope channels associated therewith. Referring now to FIG. 5, the manifold **166** can include an inlet **161**, eight outlets **163**, and a second inlet **165** positioned on an opposite end of the manifold **166**. In various embodiments, the manifold **166** can be configured to receive and distribute several different fluids throughout the operation of the endoscope reprocessor **100**. Referring to FIG. 3 once again, the inlet **161** of the manifold **166** can be configured to receive a flow of solution comprising water and detergent, among other things, from pump **162**. In various embodiments, one or more valves can be operated to place the pump **162** in fluid communication with a source of water such that the pump **162** can pump water into the supply lines **164**. In certain embodiments, one or more valves can be operated to place the pump **162** in fluid communication with a source of sterilant, or sterilant solution, such that the pump **162** can pump the sterilant into the supply lines **164**. In at least one embodiment, referring again to FIG. 5, the endoscope reprocessor **100** can comprise one or more valves, such as valve **167**, for example, which can be operated to permit a flow of pressurized air from a pressurized air source **190**, for example, into the manifold **166**. In at least one such embodiment, the pressurized air can force any remaining water, detergent, and/or sterilant out of the endoscope channels. In certain embodiments, the endoscope reprocessor **100** can further comprise a supply of alcohol **191** and a pump which can be configured to draw alcohol from the alcohol supply **191** and introduce the alcohol into the manifold **166** through the second inlet **165**, for example. In at least one such embodiment, a check valve **192** can be positioned intermediate such a pump and the second inlet **165** such that other fluids from the manifold **166** cannot flow into the alcohol supply **191**.

In view of the above, an instrument reprocessor can be configured to supply one or more pressurized fluids to the channels of an instrument, such as an endoscope, for example. In various embodiments, the flow rates of the fluids being supplied to the endoscope channels can be monitored. In the event that the flow rate of the fluid being supplied to an endoscope channel is below a target flow rate or a minimum acceptable flow rate, the instrument reprocessor can increase the flow rate of the fluid flowing therethrough. In the event that the flow rate of the fluid being supplied to an endoscope channel is above a target flow rate or a maximum acceptable flow rate, the instrument reprocessor can decrease the flow rate of the fluid flowing therethrough. In certain embodiments, the instrument reprocessor can include a plurality of supply lines supplying the endoscope channels with fluid wherein each supply line can include a variable valve orifice which can be modulated to adjust the flow rate of the fluid passing therethrough. In various embodiments, the variable valve orifice of each supply line can be part of a closed loop arrangement which includes a fixed orifice pressure differential sensor configured to sense the flow rate of the fluid. In various embodiments, the pressure differential sensor can be positioned upstream with respect to the variable valve orifice and

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downstream with respect to a circulation pump. In at least one embodiment, the instrument reprocessor can further include a gauge pressure sensor for sensing the gauge pressure of the fluid exiting the circulation pump and a pressure control system which can be configured to modulate the pressure of the fluid relative to a targeted pressure. In at least one such embodiment, the differential pressure sensor can be positioned downstream with respect to the gauge pressure sensor and the pressure control system.

As described above, the fluid circulation system of the endoscope reprocessor **100** can be configured to circulate a fluid through an endoscope and/or spray the fluid onto the outside surface of the endoscope. In various embodiments, referring now to FIG. **8**, the endoscope reprocessor **100** can comprise a fluid dispensing system **200** which can be configured to dispense one or more fluids to the fluid circulation system. In various embodiments, referring now to FIGS. **12-16**, the fluid dispensing system **200** can comprise two or more separate fluid dispensing subsystems, such as fluid dispensing subsystems **200a** and **200b**, for example, which can each be configured to dispense a different fluid, for example, to the fluid circulation system. In various embodiments, referring now to FIG. **16**, the endoscope reprocessor **100** can include a storage area which can be configured to house one or more containers of a fluid, such as sterilant container **201a** and/or detergent container **201b**, for example, wherein the endoscope reprocessor **100** can further include one or more fluid connectors which can each be sealingly engaged with one of the fluid containers. In certain embodiments, the endoscope reprocessor **100** can further comprise a RFID reader and/or a bar code reader which can be configured to read a RFID tag and/or a bar code on the fluid container to ensure that, one, the correct fluid is being used and, two, that the fluid is being used by a certain expiration date, for example. In any event, once the fluid connector has been coupled to the fluid container, the fluid dispensing system **200** can be configured to draw the fluid from the fluid container and dispense it into the circulation system, as described in greater detail further below.

In various embodiments, further to the above, the fluid subsystem **200a** can include a supply pump **210**, a reservoir **220**, and a dispensing pump **230**. In certain embodiments, the supply pump **210** can include an inlet **211** in fluid communication with the fluid container and/or any other suitable fluid source. In at least one embodiment, the supply pump **210** can comprise a positive displacement pump which, in at least one such embodiment, can comprise a piston configured to displace a fixed amount of volume, or fluid, per stroke of the piston. More specifically, referring primarily to FIG. **14**, the supply pump **210** can comprise a piston **212** which can be configured to move, or reciprocate, within a cylinder **213** between a first, or bottom dead center (BDC) position, and a second, or top dead center (TDC) position, in order to draw fluid into the cylinder **213** and push the fluid through cylinder outlet **214**. In certain embodiments, the supply pump **210** can further comprise a valve lifter **215** which can be contacted by the piston **212** to open a valve element and allow the fluid to exit through the pump outlet **214** when the piston **212** reaches its TDC position. When the piston **212** is returned to its BDC position, a valve spring positioned behind the valve lifter **215**, for example, can be configured to return the valve element and the valve lifter **215** to a seated position in which the outlet **214** is sealingly closed until the valve element and the valve lifter **215** are lifted once again by the piston **212** during the next stroke thereof. As described in greater detail

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below, the outlet **214** of the supply pump **210** can be in fluid communication with the reservoir **220** such that the fluid pressurized by the supply pump **210** can be discharged into an internal cavity **221** defined in the reservoir **220**.

In various embodiments, the reservoir **220** can include a bottom portion **222**, a housing **223**, and a top portion **224**, wherein, in at least one embodiment, the outlet **214** of the supply pump **210** can be in fluid communication with the internal cavity **221** of the reservoir **220** through a port **228** the bottom portion **222**, for example. In other various embodiments, the supply pump **210** can be in fluid communication with the reservoir cavity **211** through a port in the housing **223** and/or the top portion **224**, for example. In any event, the bottom portion **222** and the top portion **224** can be sealingly engaged with the housing **223** wherein, in at least one embodiment, the bottom portion **222** and the top portion **224** can be configured to engage the housing **223** in a snap-fit and/or press-fit arrangement, for example. In various embodiments, the bottom portion **222** and the top portion **224** can be comprised of a plastic material which may not be degraded by the fluid contained within the reservoir **220**, for example. In certain embodiments, the reservoir **220** can further include a seal, such as an O-ring **229**, for example, which can be positioned intermediate the bottom portion **222** and the housing **223** and a seal, such as an O-ring **229**, for example, positioned intermediate the housing **223** and the top portion **224** which can prevent fluids from leaking out of the reservoir **220**. In various embodiments, the housing **223** can be comprised of any suitable material, such as glass, for example. In at least one embodiment, the housing **223** can be comprised of borosilicate, for example, which may not be degraded by the fluid contained within the reservoir **220**.

As discussed above, the supply pump **210** can be configured to supply a fixed quantity of fluid to the internal reservoir cavity **221** for each stroke of the supply pump piston **212**. In use, the supply pump **210** can be operated a suitable number of times, or cycles, in order to fill the internal cavity **221** and/or fill the internal cavity **221** above a predetermined level, or height, within the internal cavity **221**. In certain embodiments, the reservoir **220** can include an overflow line **227** which can be configured to vent fluid back to the fluid source, for example, in the event that the reservoir **220** is overfilled. In various embodiments, referring again to FIG. **14**, the internal cavity **221** can have a bottom **225**, a top **226**, and a height defined between the bottom **225** and the top **226**. In at least one such embodiment, the internal cavity **221** can be cylindrical and can have a constant circumference along the height thereof while, in other embodiments, the internal cavity **221** can have any suitable configuration. In various embodiments, as a result of the above, each cycle of the supply pump **210** can raise the height of the fluid within the internal reservoir cavity **221** a certain, or fixed, amount. In at least one embodiment, the amount of fluid in the reservoir **220** can be maintained by operating the supply pump **210** the same number of strokes that the dispensing pump **230** has been operated, for example. In certain embodiments, the reservoir **210** can comprise a sensor, such as level sensor **240**, for example, which can be configured to detect the height of the fluid within the reservoir cavity **221** and/or changes in the height of the fluid within the reservoir cavity **221**, as described in greater detail below.

In various embodiments, further to the above, the level sensor **240** can comprise an analog sensor and can be mounted to the reservoir housing **223**. In at least one embodiment, the housing **223** can be comprised of glass and the level sensor **240** can be attached to the glass using at least

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one adhesive, for example. In at least one such embodiment, the level sensor can comprise a capacitive sensor, such as a linear capacitive sensor, for example, which can have a first end **241** positioned at or adjacent to the bottom **225** of the reservoir cavity **221** and a second end **242** positioned at or adjacent to the top **226** of the reservoir cavity **221**. In such embodiments, the level sensor **240** can be configured to generate a first, or low, voltage when the internal cavity **211** is empty, or at least substantially empty, and a second, or high, voltage when the internal cavity **211** is full, or at least substantially full. In addition, the level sensor **240** can be configured to generate a range of voltages between the low voltage and the high voltage, depending on the level of the fluid within the reservoir cavity **211**. More particularly, in various embodiments, the voltage generated by the level sensor **240** can be a function of the fluid height within the reservoir cavity **221** and, thus, the voltage can increase as the fluid height increases. In at least one such embodiment, the voltage can be linearly proportional to the fluid height, for example, wherein, in at least one embodiment, the low voltage can be approximately zero volts and the high voltage can be approximately five volts, for example.

In various embodiments, the fluid dispensing subsystem **200a** can further comprise a dispensing pump **230** which can be in fluid communication with the internal cavity **211** of the reservoir **210** and can be configured to draw the fluid from the reservoir cavity **211** and dispense the fluid into the fluid circulation system, and/or a mixing chamber within the fluid circulation system, of the endoscope reprocessor **100**. In at least one embodiment, the inlet to the dispensing pump **230** can be in fluid communication with the bottom **225** of the internal chamber **221** through a port **238** in the bottom portion **222** of the reservoir **220**. In certain embodiments, the dispensing pump **230** can comprise a positive displacement pump which can be configured to displace a fixed volume of fluid per stroke. A positive displacement pump is described in detail in connection with the supply pump **210** and such discussion is not repeated herein for the sake of brevity. In some embodiments, the supply pump **210** and the dispensing pump **230** can be identical, or at least nearly identical. In at least one embodiment, the dispensing pump **230** can be configured to displace the same, or at least substantially the same, amount of volume, or fluid, per stroke as the supply pump **210**.

In use, the supply pump **210** can be operated to fill the internal chamber **221** of the reservoir **220** until the fluid level has met or exceeded a predetermined height within the chamber **221**. In various embodiments, the fluid dispensing subsystem **200a** can comprise a computer, or microprocessor, such as PCB assembly **250**, for example, which can be in electrical and/or signal communication with the supply pump **210**, the dispensing pump **230**, and/or the level sensor **240**. In at least one such embodiment, the PCB assembly **250** can be configured to detect the voltage potential generated by the level sensor **240** and calculate the fluid height within the reservoir **220** as a function of the voltage potential. In the event that the PCB assembly **250** calculates that the fluid level within the reservoir **220** is below the predetermined height, the PCB assembly **250** can operate the fluid supply pump **210** until the fluid level has met or exceeded the predetermined height. In at least one embodiment, the PCB assembly **250** may not operate the dispensing pump **230** when the fluid level in the reservoir **220** is below the predetermined height. In the event that the PCB assembly **250** calculates that the fluid level in the reservoir **220** is at or above the predetermined height, the PCB assembly **250** can operate the dispensing pump **230** to supply the fluid

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circulation system with the fluid, when needed. In certain embodiments, the PCB assembly **250** can be configured to operate the supply pump **210** in advance of operating the dispensing pump **230** such that a sufficient supply of fluid exists in the reservoir **220** before the dispensing pump **230** is operated. In at least one embodiment, the PCB assembly **250** can be configured to operate the supply pump **210** after operating the dispensing pump **230** in order to replenish the supply of fluid within the reservoir **220**. In various embodiments, the PCB assembly **250** can be configured to operate the dispensing pump **230** and the supply pump **210** simultaneously such that the fluid in the reservoir **220** can be replenished as it is being dispensed by the dispensing pump **230**.

As outlined above, the supply pump **210** can comprise a positive displacement pump and, in such embodiments, the PCB assembly **250** can be configured to monitor whether the supply pump **210** is delivering a correct amount of fluid to the reservoir **220** per stroke of the pump piston **212**. More specifically, information regarding the fixed volumetric displacement of the supply pump **210** can be programmed within the PCB assembly **250** such that the PCB assembly **250** can evaluate whether the increase in fluid volume within the reservoir **220** per stroke of the supply pump **210**, as measured by the fluid level sensor **240**, matches the volumetric displacement of the supply pump **210**. In the event that the increase in fluid within the reservoir **220** per stroke of the supply pump **210**, as measured by the fluid level sensor **240**, is equal, or at least sufficiently equal, to the fixed volumetric displacement of the supply pump **210**, the PCB assembly **250** may signal to the operator of the endoscope reprocessor **100** that the supply pump **210** is being sufficiently supplied with fluid from the fluid source. In the event that the increase in fluid within the reservoir **220** per stroke of the supply pump **210**, as measured by the fluid level sensor **240**, is not equal, or at least sufficiently equal, to the fixed volumetric displacement of the supply pump **210**, the PCB assembly **250** may signal to the operator of the endoscope reprocessor **100** that the supply pump **210** is not being sufficiently supplied with fluid from the fluid source and that the fluid source may need to be examined as the fluid source may be empty, for example. In various circumstances, examining the fluid source may include replacing or replenishing the fluid source. In various embodiments, the reservoir **220** can contain a quantity of fluid therein which can be sufficient to supply the endoscope reprocessor **100**, as needed, while the operator examines the fluid supply. In previous endoscope reprocessors, the fluid circulation systems thereof drew fluid directly from the fluid supply and, thus, the endoscope reprocessor could not identify that the fluid source had been depleted until an operating cycle had already begun and the lack of fluid had interrupted the operating cycle.

In various embodiments, further to the above, the endoscope reprocessor **100** can comprise two basins **110**, for example, which can each be configured such that an endoscope can be cleaned, disinfected, and/or sterilized therein. In certain embodiments, referring again to FIG. **16**, the endoscope reprocessor **100** can comprise a separate fluid circulation system, such as circulation systems **290a** and **290b**, for example, for supplying fluid to each basin **110**. In such embodiments, the fluid dispensing subsystem **200a** can be configured to supply both of the fluid circulation systems **290a**, **290b** with fluid from fluid source **201a** and, similarly, the fluid dispensing subsystem **200b** can be configured to supply both of the fluid circulation systems **290a**, **290b** with fluid from fluid source **201b**. In at least one such embodi-

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ment, the endoscope reprocessor **100** can comprise a valve **280a** which can be, one, in fluid communication with the dispensing pump **230** of the fluid dispensing subsystem **200a** and, two, in selective fluid communication with fluid circulation systems **290a**, **290b** such that a fluid can be selectively supplied to the fluid circulation systems **290a**, **290b** from the fluid source **201a**. Similarly, the endoscope reprocessor **100** can comprise a valve **280b** which can be, one, in fluid communication with the dispensing pump **230** of the fluid dispensing subsystem **200b** and, two, in selective fluid communication with fluid circulation systems **290a**, **290b** such that a fluid can be selectively supplied to the fluid circulation systems **290a**, **290b** from the fluid source **201b**. Prior to running an operating cycle of a fluid circulation system, in certain embodiments, the fluid circulation system may require a quantity of the fluid, such as a detergent and/or sterilant, for example, from the fluid dispensing subsystem **200a**. In such embodiments, further to the above, the PCB assembly **250** can be programmed to maintain a quantity of fluid within the reservoir **220** of the subsystem **200a** such that, when fluid is needed to supply a fluid circulation system **290a**, **290b**, the fluid is available without having to operate the supply pump **210**. In various circumstances, the quantity of fluid needed from a reservoir **220** by the fluid circulation system can be larger than the volume of fluid that can be supplied by a single stroke of the dispensing pump **230** and, thus, multiple strokes of the dispensing pump **230** may be required. In any event, the quantity of a particular fluid needed by a fluid circulation system prior to an operating cycle of the instrument reprocessor **100** may equal the minimum amount of fluid that the PCB assembly **250** may be programmed to maintain in a reservoir **220**. In certain embodiments, the PCB assembly **250** may be programmed to maintain enough fluid in a reservoir **220** to supply both of the fluid circulations systems with a particular fluid to begin their operating cycles without needing to be refilled by the corresponding supply pump **210**. Of course, further to the above, the supply pump **210** could then be operated to refill the reservoir **220** after both of the fluid circulation systems have been supplied with a sufficient quantity of fluid. In light of the above, in various embodiments, a reservoir **220** may have enough fluid contained therein to supply at least one operating cycle of a fluid circulation system prior to the corresponding supply pump **210** being activated to refill the reservoir **220** wherein, in the event that the supply pump **210** is unable to refill the reservoir **220** due to an empty fluid supply, for example, the operator of the endoscope reprocessor **100** is afforded an opportunity to replace the fluid supply prior to the next operating cycle of a fluid circulation system.

Further to the above, the dispensing pump **230** can comprise a positive displacement pump and, in such embodiments, the PCB assembly **250** can monitor whether the dispensing pump **230** is drawing a correct amount of fluid per stroke from the reservoir **220**. More specifically, information regarding the fixed volumetric displacement of the dispensing pump **230** can be programmed within the PCB assembly **250** such that the PCB assembly **250** can evaluate whether the decrease in fluid within the reservoir **220** per stroke of the dispensing pump **230**, as measured by the fluid level sensor **240**, matches the fixed volumetric displacement of the dispensing pump **230**. In the event that the decrease in fluid within the reservoir **220** per stroke of the dispensing pump **210** is equal, or at least sufficiently equal, to the fixed volumetric displacement of the dispensing pump **230**, as measured by the fluid level sensor **240**, the PCB assembly **250** may signal to the operator of the endo-

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scope reprocessor **100** that the dispensing pump **230** is being sufficiently supplied with fluid from the reservoir **220**. In the event that the decrease in fluid within the reservoir **220** per stroke of the dispensing pump **230**, as measured by the fluid level sensor **240**, is not equal, or at least sufficiently equal, to the volumetric displacement of the dispensing pump **230**, the PCB assembly **250** may signal to the operator of the endoscope reprocessor **100** that the dispensing pump **230** is not being sufficiently supplied with fluid and that some examination and/or maintenance of the fluid dispensing subsystem may be required.

As discussed above with regard to various embodiments, each fluid dispensing subsystem **200a**, **200b** can comprise a fluid supply pump **210** and a separate fluid dispensing pump **230**. As also discussed above, in various embodiments, the fluid supply pump **210** and the fluid dispensing pump **230** can be operated independently of one another to supply fluid to and dispense fluid from the reservoir **220**, respectively. In certain alternative embodiments, a single pumping apparatus can be configured to, one, pump fluid into the reservoir **220** from the fluid supply and, two, pump fluid from the reservoir **220** into a fluid circulation system. In at least one such embodiment, the pumping apparatus can comprise a piston having a first piston head positioned within a first cylinder and a second piston head positioned within a second cylinder wherein the piston can be reciprocated linearly to move the first and second piston heads within the first and second cylinders, respectively. In various embodiments, the first cylinder can be in fluid communication with a fluid source and the reservoir while the second cylinder can be in fluid communication with the reservoir and the fluid circulation system such that the first piston head moving within the first cylinder can pump fluid from the fluid source into the reservoir and the second piston head moving within the second cylinder can pump fluid from the reservoir into the fluid circulation system. In various embodiments, the arrangement of the first piston head and the first cylinder can comprise a first positive displacement pump and the arrangement of the second piston head and the second cylinder can comprise a second positive displacement pump. In certain embodiments, the pumping apparatus can comprise a valve control system which can be configured to control or limit the flow of fluid into the first cylinder and/or the second cylinder, for example. In at least one such embodiment, the valve control system can be configured to close a valve element and prevent fluid from flowing into the second cylinder while fluid is being pumped into the reservoir from the first cylinder. Similarly, the valve control system can be configured to close a valve element and prevent fluid from flowing into the first cylinder while fluid is being pumped from the reservoir through the second cylinder. In such embodiments, the first and second piston heads may be reciprocate within their respective first and second cylinders; however, the flow of fluid through of the cylinders may be prevented, as described above. In various alternative embodiments, a pump can comprise a rotary pump having a first aperture in fluid communication with the fluid source, a second aperture in fluid communication with the reservoir, and a third aperture in fluid communication with the fluid circulation system. In at least one such embodiment, a valve control system can be configured to close or block the third aperture when pumping fluid into the reservoir and, alternatively, block the first aperture when pumping fluid from the reservoir. In certain embodiments, the valve control system could include any suitable arrangement of one or more shuttle valves and/or spool valves, for example. In various embodiments, any suitable positive displacement

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pump including a three-way valve could be utilized to pump fluid into the reservoir **220** from a fluid source and then from the reservoir **220** into the fluid circulation system.

As discussed above, referring again to FIG. **16**, the endoscope reprocessor **100** can comprise a fluid dispensing system **200** which can be configured to supply a fluid to one or more fluid circulation systems. As also discussed above, the fluid dispensing system **200** can comprise more than one fluid dispensing subsystem, such as first subsystem **200a** and second subsystem **200b**, for example. In various embodiments, the second subsystem **200b** can be identical, or at least substantially identical, to the first subsystem **200a** and, as a result, the structure and operation of the second subsystem **200b** is not repeated herein for the sake of brevity. In at least one embodiment, the first subsystem **200a** can be configured to dispense a first fluid to one or more fluid circulation systems, such as fluid circulation systems **290a** and **290b**, for example, and the second subsystem **200b** can be configured to dispense a second fluid to the fluid circulation systems **290a**, **290b**, for example. In at least one such embodiment, the first fluid dispensing subsystem **200a** can be configured to dispense a detergent, for example, to a fluid circulation system while the second fluid dispensing subsystem **200b** can be configured to dispense a sterilant, such as peracetic acid, for example, to the fluid circulation system. As also discussed above, the fluid dispensing systems **200a** and **200b** may be operated at different times to supply the fluid circulation systems with their respective fluids at different times during the operating cycles thereof. In various other circumstances, the fluid subsystems **200a** and **200b** can be operated at the same time to supply the same fluid circulation system with different fluids and/or at the same time to supply different fluid circulation systems with different fluids, for example.

Further to the above, the first fluid circulation system **290a** can comprise a first channel flow subsystem **160** and a first pump **162** for circulating a fluid through the first circulation system **290a** while the second fluid circulation system **290b** can comprise a second channel flow subsystem **160** and a second pump **160** for circulating a fluid through the second circulation system **290b**. In various other embodiments, an instrument reprocessor may comprise any suitable number of fluid circulation systems; however, with regard to any one of the fluid circulation systems, the channel flow subsystem **160** thereof can be configured to control an initialization, or start-up, procedure of the fluid circulation system. More specifically, after an instrument has been placed in a basin **110** and the lid **130** has been closed, the operator can initialize an operating cycle to clean the instrument and, at such point, the channel flow subsystem **160** can be configured to control the initial flow of reprocessing fluid from the pump **162**. In various embodiments, the instrument, such as an endoscope, for example, can comprise a plurality of channels, or lumens, extending therethrough which can have different lengths, diameters, and/or configurations, for example, which can cause the channels to have different overall flow resistances, or restrictions, for example. In the event that pump **162** were to be initialized with all of the proportional valves **174** in an open condition and/or the same condition, the fluid flowing from the pump **162** would tend to fill and/or pressurize the channels of the endoscope having lower flow resistances before filling and/or pressurizing the endoscope channels having higher flow resistances, for example. In various circumstances, such a situation would be transient and the desirable operating conditions or steady state operating conditions of the fluid circulation system would eventually

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be reached. In some circumstances, this start-up procedure is entirely suitable. In other circumstances, however, a different start-up procedure may be desirable.

In various embodiments, further to the above, the channel flow subsystem **160** can include a computer and/or a micro-processor, for example, which can arrange the valves **174** in different conditions during the initialization procedure. In at least one embodiment, the subsystem computer can operate the valves **174** to compensate for the different flow resistances, or restrictions, of the endoscope channels, for example. For instance, for the valves **174** that control the flow of fluid through the high flow resistance endoscope channels, the subsystem computer can place such valves **174** in a fully open condition while, for the valves **174** that control the flow of fluid through the low fluid resistance endoscope channels, the subsystem computer can place such valves **174** in a partially closed condition. In such embodiments, the flow of fluid from the pump **162** may tend to fill and/or pressurize all of the endoscope channels at the same time, or at least substantially the same time. In certain circumstances, the transient state for filling the channels with pressurized fluid may be shortened and a steady state operating condition, or a desirable operating condition, can be reached in less time. Such embodiments may reduce the overall time needed to run a cleaning cycle of the instrument reprocessor **100**. In embodiments having eight endoscope channels and eight flow control units **170** for controlling the flow of fluid through eight corresponding channel supply lines **164**, for example, the eight proportional valves **174** thereof can all be placed in different conditions, and/or the same condition, of being open, closed, partially open, and/or partially closed, for example.

In various embodiments described herein, the flow subsystem computer can utilize one or more criteria, or parameters, for controlling the valves **174** of the flow control units **170** during the initialization, or start-up, procedure. Further to the above, a first proportional valve **174** of a first control unit **170** can be configured to control the fluid flow through a first endoscope channel defined by a first value of a particular parameter, a second proportional valve **174** of a second control unit **170** can be configured to control the fluid flow through a second endoscope channel defined by a second value of the particular parameter, and a third proportional valve **174** of a third control unit **170** can be configured to control the fluid flow through a third endoscope channel defined by a third value of a particular parameter. In various embodiments, the first value of the parameter can be larger than the second value of the parameter and the second value can be larger than the third value of the parameter wherein the first valve **174** can be modulated to a first open state, the second valve **174** can be modulated to a second open state based on the difference between the first value and the second value of the parameter, and the third valve **174** can be modulated to a third open state based on the difference between the first value and the third value of the parameter in order to regulate the flow of fluid through the first, second, and third channels. In at least one such embodiment, the first open state, the second open state, and the third open state of the first, second, and third valves **174**, respectively, can be selected such that, during the initialization, or start-up, procedure of the fluid circulation system, the flow of fluid through the first, second, and third endoscope channels can be evenly, or at least substantially evenly distributed, across the first, second, and third endoscope channels. In at least one embodiment, the first, second, and third open states of the valves **174** can be selected such that the volumetric flow rates through the

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endoscope channels are equal, or at least substantially equal, to one another as the endoscope channels fill with fluid. In such an embodiment, the fluid flow rates through the endoscope channels can increase during the initialization procedure wherein each fluid flow can increase concurrently with the other fluid flows. In at least one embodiment, the first, second, and third open states of the valves **174** can be selected such that the gauge pressure of the fluid flowing through the endoscope channels are equal, or at least substantially equal, to one another as the endoscope channels fill with fluid. In such an embodiment, the pressure or the fluid flowing through the endoscope channels can increase during the initialization procedure wherein the pressure of each fluid flow can increase concurrently with the pressure of the other fluid flows.

In at least one embodiment, further to the above, the parameter for selecting the open conditions of the proportional valves **174** can comprise the flow resistance values of the instrument channels. In various circumstances, the flow resistance value of an instrument channel can be influenced by many variables; however, the flow resistance value of an instrument channel can be largely determined by the channel length, the channel diameter, and the curves, or bends, in the channel path. Instrument channels having longer lengths, smaller diameters, and/or more curves in the channel path will typically have higher flow resistance values than instrument channels having shorter lengths, larger diameters, and/or less curves in the channel path. In any event, the instrument channel having the highest flow resistance value of the medical instrument can be selected as a baseline from which the fluid flows through the other instrument channels can be adjusted. In at least one embodiment, the first instrument channel can have the highest fluid flow resistance and the first proportional valve **174** can be set to a fully open condition, for example. In various embodiments, the second proportional valve **174** can be closed a certain amount based on the difference between the first flow resistance value and the second flow resistance value. Similarly, the third proportional valve **174** can be closed a certain amount based on the difference between the first flow resistance value and the third flow resistance value. In various circumstances, the larger the difference between the flow resistance value of an instrument channel and the first flow resistance value, or a baseline flow resistance value, the greater degree in which the corresponding proportional valve **174** can be closed.

In any event, further to the above, once the steady state operating condition, or the desirable operating condition, of the fluid circulation system has been reached, the subsystem computer can permit the flow control units **170** to independently control and govern the flow of fluid through the endoscope channel supply lines **164** as discussed above. In various circumstances, the devices and methods described herein can be designed to provide an adequate supply of reprocessing fluid to clean, disinfect, and/or sterilize an endoscope, and/or any other suitable instrument, comprising channels having different flow resistances. Further to the above, these devices and methods can be configured to supply an adequate supply of reprocessing fluid to the channels by controlling the fluid flow through each channel individually.

In various circumstances, the pump **162** can have a sufficient output to supply all of the reprocessor supply lines **164** and the endoscope channels associated therewith with an adequate supply of reprocessing fluid during the initialization of the operating cycle and throughout the operating cycle. Further to the above, the flow control units **170** can be configured to manage the fluid supplied thereto such that

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each reprocessor supply line **164** has a flow rate there-through which meets or exceeds the minimum target flow rate and, thus, is not starved for fluid. In the event that the fluid flow through one or more of the reprocessor supply lines **164** is below the minimum target flow rate and the pump **162** is not operating at maximum capacity, the output of the pump **162** can be increased. In some circumstances, the gauge pressure of the reprocessing fluid exiting the pump **162** can increase above the target gauge pressure, such as 35 psig, for example, at least temporarily in order for the pump **162** to meet the supply demands of the reprocessor supply lines **164** and the endoscope channels associated therewith. In the event that the fluid flow through one or more of the reprocessor supply lines **164** is below the minimum target flow rate and the pump **162** is operating at a maximum, or near maximum, capacity, at least one booster pump could be operated to increase the flow rate and/or pressure of the reprocessing fluid entering into the manifold **166** and the reprocessor supply lines **164**. In various embodiments, the at least one booster pump could be in series with pump **162** and/or in parallel with the pump **162**, for example, wherein the at least one booster pump could be selectively operated to assist the pump **162**.

In various embodiments discussed herein, each reprocessor supply line **164** of the channel flow subsystem **160** can comprise a proportional valve **174** configured to control a variable orifice. In various other embodiments, at least one of the reprocessor supply lines **164** can include a fixed orifice or a fixed orifice valve. In at least one embodiment, the fixed orifice valve can be positionable in either an open condition or a closed condition. In at least one such embodiment, the reprocessor supply line **164** having a fixed orifice valve can be coupled to the endoscope channel having the highest fluid flow resistance, for example, wherein the fluid flow rate through such a endoscope channel may be a function of the gauge pressure of the reprocessing fluid supplied by the pump **162**. In various embodiments, the reprocessor supply lines **164** having a variable orifice controlled by a proportional valve **174**, for example, can be modulated with respect to the reprocessor supply line **164** having a fixed orifice valve when the fixed orifice valve is in an open condition, for example.

Any patent, publication, or other disclosure material, in whole or in part, that is said to be incorporated by reference herein is incorporated herein only to the extent that the incorporated materials do not conflict with existing definitions, statements, or other disclosure material set forth in this disclosure. As such, and to the extent necessary, the disclosure as explicitly set forth herein supersedes any conflicting material incorporated herein by reference. Any material, or portion thereof, that is said to be incorporated by reference herein, but which conflicts with existing definitions, statements, or other disclosure material set forth herein will only be incorporated to the extent that no conflict arises between that incorporated material and the existing disclosure material.

While this invention has been described as having exemplary designs, the present invention may be further modified within the spirit and scope of the disclosure. This application is therefore intended to cover any variations, uses, or adaptations of the invention using its general principles. Further, this application is intended to cover such departures from the present disclosure as come within known or customary practice in the art to which this invention pertains.

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What is claimed is:

1. An instrument reprocessor for cleaning an instrument, the instrument including a passage configured to receive a reprocessing fluid, the instrument reprocessor comprising:
 - a chamber configured to receive the instrument;
 - a pump configured to pressurize the reprocessing fluid and supply the reprocessing fluid to the passage, wherein the pump comprises an inlet and an outlet;
 - a gauge pressure sensor positioned to sense a gauge pressure of the reprocessing fluid flowing from the pump outlet;
 - a proportional valve configured to direct a portion of a fluid flow from the pump to a fluid feedback loop in fluid communication with a source of fluid for the pump based at least in part on a pressure value determined by the gauge pressure sensor; and
 - a flow control system, comprising:
 - a valve in fluid communication with the passage, wherein the valve is configured to control a flow rate of reprocessing fluid through the passage, and wherein the valve comprises an inlet and an outlet;
 - a pressure differential sensor configured to sense a pressure differential in the reprocessing fluid on opposite sides of a fixed orifice, wherein the pressure differential sensor is positioned upstream with respect to the valve outlet; and
 - a processor in signal communication with the pressure differential sensor, wherein the processor is configured to interpret the flow rate based on the pressure differential and command the valve to at least one of at least partially close and at least partially open.
2. The instrument reprocessor of claim 1, wherein the pressure differential sensor is positioned downstream with respect to the gauge pressure sensor.
3. A flow control system for use with a pressurized fluid channel, the flow control system, comprising:
 - a valve in fluid communication with a pressurized fluid, wherein the valve is configured to control a flow rate of the pressurized fluid through the pressurized fluid channel, and wherein the valve comprises an inlet and an outlet;
 - a first pressure differential sensor configured to sense a first pressure differential in the pressurized fluid on opposite sides of a first fixed orifice, wherein the first pressure differential sensor is positioned upstream with respect to the valve inlet;
 - a first gauge pressure sensor positioned downstream with respect to the valve outlet;
 - a pressure regulating device in fluid communication with the pressurized fluid channel;
 - a second gauge pressure sensor positioned to sense a second gauge pressure of the pressurized fluid flowing from an outlet of the pressure regulating device;
 - a proportional valve configured to direct a portion of fluid flow from the pressure regulating device to a fluid feedback loop in fluid communication with a source of fluid for the pressure regulating device based at least in part on a pressure value determined by the second gauge pressure sensor; and
 - a processor in signal communication with the first pressure differential sensor and the first gauge pressure sensor, wherein the processor is configured to interpret the flow rate based on the first pressure differential and command the valve to at least one of at least partially close and at least partially open.
4. The flow control system of claim 3, wherein the pressure regulating device comprises a pump.

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5. The flow control system of claim 3, further comprising a second pressure differential sensor configured to sense a second pressure differential in the pressurized fluid on opposite sides of a second fixed orifice,
 - wherein the second pressure differential sensor is disposed fluidically in parallel with the first pressure differential sensor, and
 - wherein the second pressure differential sensor is in signal communication with the processor.
6. The flow control system of claim 5, wherein the first pressure differential sensor transmits a first voltage reading associated with the first pressure differential to the processor,
 - wherein the second pressure differential sensor transmits a second voltage reading associated with the second pressure differential to the processor, and
 - wherein the processor is configured to execute a corrective action routine when the first voltage reading differs from the second voltage reading.
7. The flow control system of claim 6, wherein the corrective action routine comprises issuing a warning to an operator of the flow control system.
8. An instrument reprocessor for cleaning a medical instrument, the medical instrument including a passage, the instrument reprocessor comprising:
 - a chamber configured to receive the medical instrument;
 - a supply connector configured to be fluidly coupled with the passage;
 - a pump configured to pressurize a reprocessing fluid and supply the reprocessing fluid to the supply connector, wherein the pump comprises an inlet and an outlet;
 - a first gauge pressure sensor positioned to sense a first gauge pressure of the reprocessing fluid flowing from the pump outlet;
 - a proportional valve configured to direct a portion of a fluid flow from the pump to a fluid feedback loop in fluid communication with a source of fluid for the pump based at least in part on the first gauge pressure; and
 - at least one flow control system, comprising:
 - a valve in fluid communication with the supply connector, wherein the valve is configured to control a flow rate of reprocessing fluid through the passage, and wherein the valve comprises an inlet and an outlet;
 - a first pressure differential sensor configured to sense a first pressure drop in the reprocessing fluid on opposite sides of a first fixed orifice, wherein the first pressure differential sensor is positioned downstream with respect to the first gauge pressure sensor and upstream with respect to the valve outlet;
 - a second pressure differential sensor configured to sense a second pressure drop in the reprocessing fluid on opposite sides of a second fixed orifice, wherein the second pressure differential sensor is disposed fluidically in parallel with the first pressure differential sensor;
 - a second gauge pressure sensor positioned downstream with respect to the valve outlet; and
 - a processor in signal communication with the first pressure differential sensor, the second pressure differential sensor, and the second gauge pressure sensor, wherein the processor is configured to interpret the flow rate based on the first pressure drop and command the valve to at least one of at least partially close and at least partially open.

9. The instrument reprocessor of claim 8, wherein the processor is configured to interpret a first flow rate based on the first pressure drop and a second flow rate based on the second pressure drop, and

wherein the processor is configured to execute a correc- 5
tive action routine when the first flow rate differs from
the second flow rate.

10. The instrument reprocessor of claim 8, wherein the at least one flow control system comprises a plurality of flow control systems. 10

11. The instrument reprocessor of claim 10, where at least one flow control system of the plurality of flow control systems is fluidically and electrically independent of at least a second flow control system of the plurality of flow control systems. 15

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